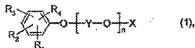


Claims

1. A composition comprising

(A) 75 - 95 % by weight of a compound of formula (1)

5



wherein R_1 , R_2 , R_3 and R_4 independently of the other denote hydrogen, C_1 - C_{12} alkyl, C_6 - C_{10} -aryl or C_8 - C_{12} alkaryl, Y represents ethylene or propylene, n is a number from 4 to 50 and X denotes hydrogen, C_1 - C_{12} alkyl, the acid radical of an inorganic oxygen

10 containing acid or the radical of an organic acid, and

(B) 5 - 25 % by weight of a formaldehyde condensation product prepared from an aromatic sulfonic acid and formaldehyde,

the total amount of components (A) + (B) being 100 % by weight.

15 2. A composition according to claim 1 containing as component (A) a compound of the formula (1), wherein

R_1 is C_2 - C_{12} alkyl, phenyl, tolyl, phenyl- C_1 - C_3 alkyl or tolyl- C_1 - C_3 alkyl,

R_2 and R_3 are, independently from the other, hydrogen, C_2 - C_{12} alkyl, phenyl, tolyl, phenyl- C_1 - C_3 alkyl or tolyl- C_1 - C_3 alkyl,

20 R_4 is hydrogen, X is an acid radical derived from sulfuric acid or orthophosphoric acid, Y represents ethylene and n is a number from 4 to 40.

3. A composition according to claim 1 containing as component (A) a compound of the formula (1), wherein R_1 is 1-phenylethyl, R_2 and R_3 are, independently from the other,

25 hydrogen or 1-phenylethyl, R_4 is hydrogen, Y represents ethylene and n is a number from 12 to 30.

4. A composition according to claim 1 containing as component (A) the ethanalamine, diethanalamine, triethanalamine, ammonium, potassium or sodium salt of a mixture of

30 monoester and diester phosphate of the polyadduct of 12 to 18 mol of ethylene oxide with the adduct of 1 to 3 mol of styrene with 1 mol of phenol.

Author Search

=> FILE HCAPLUS

FILE 'HCAPLUS' ENTERED AT 09:36:29 ON 18 APR 2009

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PLEASE SEE "HELP USAGETERMS" FOR DETAILS.

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FILE COVERS 1907 - 18 Apr 2009 VOL 150 ISS 17

FILE LAST UPDATED: 17 Apr 2009 (20090417/ED)

HCAPlus now includes complete International Patent Classification (IPC) reclassification data for the third quarter of 2008.

CAS Information Use Policies apply and are available at:

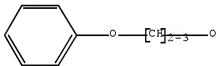
<http://www.cas.org/legal/infopolicy.html>

This file contains CAS Registry Numbers for easy and accurate substance identification.

'OBI' IS DEFAULT SEARCH FIELD FOR 'HCAPLUS' FILE

=> D STAT QUE L79

L10 STR



Structure attributes must be viewed using STN Express query preparation.

L13 SCR 2043

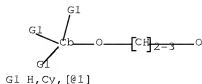
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Structure attributes must be viewed using STN Express query preparation.

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L79 ANSWER 1 OF 1 HCAPLUS COPYRIGHT 2009 ACS on STN
 ACCESSION NUMBER: 2005:564786 HCAPLUS Full-text
 DOCUMENT NUMBER: 143:79629
 TITLE: Dispersant compositions for reduction of differential
 pressure in aqueous static dyeing of textiles
 INVENTOR(S): Bailey, Byron Scott, Sr.; Griffin,

Serial No.:10/582,307

Bruce Owen; Lyons, Brenda W.;
Weber, Martin; Saretto, Bruno;
Schlingmann, Reinrich; Mahler, Georges
Ciba Specialty Chemicals Holding Inc., Switz.
PCT Int. Appl., 14 pp.
CODEN: PIXXD2

PATENT ASSIGNEE(S):
SOURCE:

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LANGUAGE:

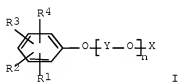
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PATENT INFORMATION:

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PRIORITY APPLN. INFO.:			US 2003-529371P	P 20031211 <--
			WO 2004-EP53190	W 20041201 <--

ED Entered STN: 30 Jun 2005

GI



AB A composition comprises (a) 75-95% of a compound of the general formula (I), where R1, R2, R3 and R4 are independently hydrogen, C1-C12-alkyl, C5-C24-aryl, or C6-C36-aralkyl; Y is ethylene or propylene; n is a number from 4 to 50; X is hydrogen, C1-C12-alkyl, a radical of an inorg. oxygen-containing acid, or a radical of an organic acid, and (b) 5-25% of a condensation product of an aromatic sulfonic acid and formaldehyde, the total amount of components (a) and (b) being 100%. The comps. can be used as dispersants in aqueous static dyeing of textiles substantially reducing or eliminating differential pressure

when combined with UV absorbers of the benzotriazole, benzotriazine and benzophenone-type. Thus, a dispersant composition having good storage stability and viscosity of 250 mPas was produced by mixing deionized water (54.22), 2-(2'-hydroxy-3'-tert-butyl-5'-methylphenyl)-5-chlorobenzotriazole (12.5), an addition product of tris(1-phenylethyl)phenol and 16 mol of ethylene oxide (7.7), sulfonated ditolyl ether-formaldehyde condensate (2.1), an addition product of C16-18-alkyl alc. and 25 mol of ethylene oxide (0.7), and a com. defoaming agent (1.0), dispersing the composition to a particle size < 2.5 μ m, and adding a xanthan gum-based thickening agent (0.4), fungicide Proxel GXL (0.38), and deionized water (25.0 g).

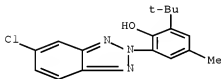
IT 3896-11-5

RL: MOA (Modifier or additive use); USES (Uses)

(UV absorber; dispersant compns. for reduction of differential pressure in aqueous static dyeing of textiles)

RN 3896-11-5 HCAPLUS

CN Phenol, 2-(5-chloro-2H-benzotriazol-2-yl)-6-(1,1-dimethylethyl)-4-methyl- (CA INDEX NAME)



IT 50-00-0D, Formaldehyde, polymers with sulfonated aromatic compds.

70559-25-0

RL: NUU (Other use, unclassified); TEM (Technical or engineered material use); USES (Uses)

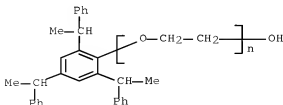
(dispersing agent; dispersant compns. for reduction of differential pressure in aqueous static dyeing of textiles)

RN 50-00-0 HCAPLUS

CN Formaldehyde (CA INDEX NAME)



RN 70559-25-0 HCAPLUS

CN Poly(oxy-1,2-ethanediyl), α -[2,4,6-tris(1-phenylethyl)phenyl]- ω -hydroxy- (CA INDEX NAME)

Serial No.:10/582,307

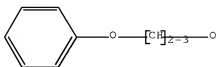
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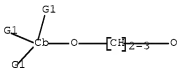
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Ak¹



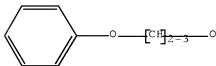
G1 H, Cy, [81]

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L58 515 SEA FILE=HCAPLUS SPE=ON ABB=ON PLU=ON L57 AND (PRY<=2004 OR
AY<=2004 OR PY<=2004)
L62 6707 SEA FILE=HCAPLUS SPE=ON ABB=ON PLU=ON UV STABILIZERS/CT
L63 163 SEA FILE=HCAPLUS SPE=ON ABB=ON PLU=ON L58 AND L62
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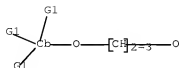
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Ak¹



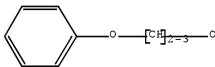
G1 H, Cy, [81]

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 AY<=2004 OR PY<=2004)
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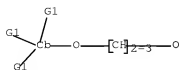
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G1 H, Cy, [81]

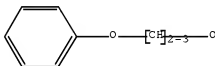
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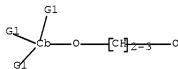


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Ak¹



G1 H,Cy, [81]

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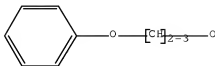
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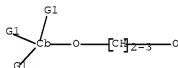
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L34 STR

Ak¹

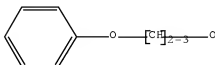


G1 H,Cy, [81]

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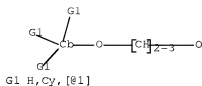


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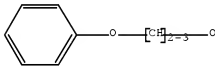
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L65	2052	SEA FILE=HCAPLUS SPE=ON	ABB=ON PLU=ON	DISPERSE DYES+RT/CT
L66	24655	SEA FILE=HCAPLUS SPE=ON	ABB=ON PLU=ON	DISPERSING AGENTS/CT
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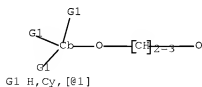
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Structure attributes must be viewed using STN Express query preparation.

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L34	STR

Ak¹

Structure attributes must be viewed using STN Express query preparation.

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Serial No.:10/582,307

L49 23942 SEA FILE=REGISTRY SPE=ON ABB=ON PLU=ON 333.415.11/RID
 L50 21464 SEA FILE=REGISTRY SPE=ON ABB=ON PLU=ON L49 AND 46.150.18/RID
 L53 10161 SEA FILE=HCAPLUS SPE=ON ABB=ON PLU=ON L50
 L57 587 SEA FILE=HCAPLUS SPE=ON ABB=ON PLU=ON L36 AND L53
 L58 515 SEA FILE=HCAPLUS SPE=ON ABB=ON PLU=ON L57 AND (PRY<=2004 OR
 AY<=2004 OR PY<=2004)
 L62 6707 SEA FILE=HCAPLUS SPE=ON ABB=ON PLU=ON UV STABILIZERS/CT
 L63 163 SEA FILE=HCAPLUS SPE=ON ABB=ON PLU=ON L58 AND L62
 L71 9 SEA FILE=HCAPLUS SPE=ON ABB=ON PLU=ON L63 AND 40/SC, SX

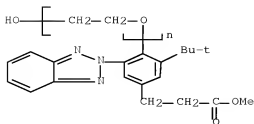
=> S L67-L69, L52, L54, L70, L71
 L83 17 (L67 OR L68 OR L69 OR L52 OR L54 OR L70 OR L71)

=> S L83 NOT L79
 L84 16 L83 NOT L79

=> D IBIB ED ABS HITSTR L84 1-16

L84 ANSWER 1 OF 16 HCAPLUS COPYRIGHT 2009 ACS on STN
 ACCESSION NUMBER: 2006:317328 HCAPLUS Full-text
 DOCUMENT NUMBER: 144:351962
 TITLE: Yellowing-resistant flexible polyurethane foams and
 their moldings
 INVENTOR(S): Ohira, Yasumasa; Nishikawa, Takahiro
 PATENT ASSIGNEE(S): Kurashiki Spinning Co., Ltd., Japan
 SOURCE: Jpn. Kokai Tokkyo Koho, 12 pp.
 CODEN: JKXXAF
 DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
	JP 2006089562	A	20060406	JP 2004-275209	20040922 <--
PRIORITY APPLN. INFO.:				JP 2004-275209	20040922 <--
ED	Entered STN: 06 Apr 2006				
AB	Title foams, obtained by reaction of polyols and organic polyisocyanates in the presence of blowing agents, foam stabilizers, catalysts, and additives, contain 0.5-7.0 parts (for 100 parts of the polyols) tetraphenyldipropylene glycol diphosphate (I). Moldings of the foams are useful for wearing apparels such as brassiere pads and shoulder pads, sanitary goods such as napkins and diapers, and cosmetics such as puffs. Thus, a composition containing glycerin-based polyether polyol, dipropylene glycol, H ₂ O, I, Tinuvin 213 (UV absorber), antioxidant, and TDI 80 was blown to give a test piece showing low change in yellowing index after exposure to NO _x .				
IT	136457-10-8, Tinuvin 213 RL: COS (Cosmetic use); MOA (Modifier or additive use); TEM (Technical or engineered material use); THU (Therapeutic use); BIOL (Biological study); USES (Uses) (UV absorbers; flexible polyurethane foams with good yellowing resistance in exposure to nitrogen oxide)				
RN	136457-10-8 HCAPLUS				
CN	Poly(oxy-1,2-ethanediyl), α -[2-(2H-benzotriazol-2-yl)-6-(1,1-dimethylethyl)-4-(3-methoxy-3-oxopropyl)phenyl]- ω -hydroxy- (CA INDEX NAME)				



L84 ANSWER 2 OF 16 HCAPLUS COPYRIGHT 2009 ACS on STN

ACCESSION NUMBER: 2005:545908 HCAPLUS [Full-text](#)

DOCUMENT NUMBER: 143:79627

TITLE: Compositions containing benzotriazole derivatives and polyoxyethylene ether sulfate salts as lightfastness improving agents for hydrophobic fibers and dyeing hydrophobic fibers using the agents therefrom

INVENTOR(S): Izutsu, Kiyosumi; Takeda, Kenji; Matsuyama, Shigeru

PATENT ASSIGNEE(S): Nippon Kayaku Co., Ltd., Japan; Nippon Kayaku Fukuyama Co., Ltd.

SOURCE: Jpn. Kokai Tokkyo Koho, 12 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

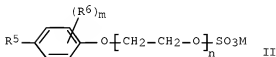
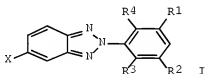
LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2005163238	A	20050623	JP 2003-406186	20031204 <--
PRIORITY APPLN. INFO.:			JP 2003-406186	20031204 <--
OTHER SOURCE(S):	MARPAT	143:79627		
ED Entered STN:	24 Jun 2005			

GI



AB The comps. (A1) comprise I (R1 = C1-12 linear or branched alkyl, cumyl; R2 = OH, C1-12 linear or branched alkyl, C1-12 linear or branched alkoxy, benzyloxy; R3 = H, OH, C1-12 linear or branched alkoxy; R4 = H, OH; X = H, Cl), and II (R5, R6 = C6-18 alkyl, stearyl, benzyl; n = 1-15; m = 0-1, M = Na, NH4), or the comps. comprise above A1 comps. having I consisting of 2-(2'-

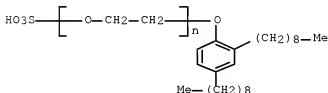
hydroxy-3'-tert-butyl-5'-methylphenyl)-5-chlorobenzotriazole (III). The lightfastness improving agents (A2) for hydrophobic fibers consist of above A1 compns. The dyed fibers are prepared by dyeing hydrophobic fibers using above A2 lightfastness improving agents, and disperse dyes and/or disperse-type cationic dyes. An aqueous composition containing 20.0% III (Tinuvin 326) and 14.4% polyethylene glycol nonylphenyl ether sulfate ammonium salt (Hitenol NE-053) was pulverized in a sand grinder for 10 h to give a dispersed composition (A3). A woven polyester tropical was dyed with a liquid containing 10 mg C.I. Disperse Blue 54 and 100 mg dispersed A3 composition for 60 min at 130°, washed, dried, and heat-treated 30 s at 180° in a pin tenter to give a dyed fabric showing lightfastness rating (JIS 0874-74, gray scale, 5 most superior rating) 4-5 on exposing the fabric to light in a fadeometer for 288 h at 89°.

IT 917952-95-5, Polyethylene glycol 2,4-dinonylphenyl ether sulfate ammonium salt

RL: MOA (Modifier or additive use); PRP (Properties); USES (Uses)
(Hitenol NE 053, dispersing agent; compns. containing benzotriazole derivs. and polyoxyethylene ether sulfate salts as lightfastness improving agents for hydrophobic fibers and dyeing hydrophobic fibers using the agents therefrom)

RN 917952-95-5 HCAPLUS

CN Poly(oxy-1,2-ethanediyl), α -sulfo- ϕ -(2,4-dinonylphenoxy)-, ammonium salt (1:1) (CA INDEX NAME)

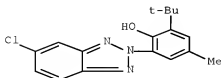


IT 3896-11-5, Tinuvin 326

RL: MOA (Modifier or additive use); PRP (Properties); USES (Uses)
(lightfastness improving agent; compns. containing benzotriazole derivs. and polyoxyethylene ether sulfate salts as lightfastness improving agents for hydrophobic fibers and dyeing hydrophobic fibers using the agents therefrom)

RN 3896-11-5 HCAPLUS

CN Phenol, 2-(5-chloro-2H-benzotriazol-2-yl)-6-(1,1-dimethylethyl)-4-methyl- (CA INDEX NAME)

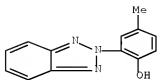


L84 ANSWER 3 OF 16 HCAPLUS COPYRIGHT 2009 ACS on STN
 ACCESSION NUMBER: 2005:141200 HCAPLUS Full-text
 DOCUMENT NUMBER: 142:254568
 TITLE: Methods and compositions for increasing the efficacy of biologically-active ingredients such as antitumor agents
 INVENTOR(S): Windsor, J. Brian; Roux, Stan J.; Lloyd, Alan M.; Thomas, Collin E.
 PATENT ASSIGNEE(S): Board of Regents, the University of Texas System, USA
 SOURCE: PCT Int. Appl., 243 pp.
 CODEN: PIXXD2
 DOCUMENT TYPE: Patent
 LANGUAGE: English
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
WO 2005014777	A2	20050217	WO 2003-US32667	20031016 <--
WO 2005014777	A3	20050915		
W:	AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, EG, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MY, NZ, OM, PG, PH, PL, PT, RO, RU, SC, SD, SE, SG, SK, SL, SY, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, YU, ZA, ZM, ZW			
RW:	GH, GM, KE, LS, MW, MZ, SD, SL, SZ, TZ, UG, ZM, AM, AZ, BY, KG, KZ, MD, RU, TJ, TM, AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HU, IE, IT, LU, MC, NL, PT, RO, SE, SI, SK, TR, BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG			
CA 2502148	A1	20050217	CA 2003-2502148	20031016 <--
AU 2003304398	A1	20050225	AU 2003-304398	20031016 <--
EP 1576150	A2	20050921	EP 2003-816736	20031016 <--
EP 1576150	A3	20051102		
R:	AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, HU, SK			
US 20060276339	A1	20061207	US 2006-531744	20060123 <--
PRIORITY APPLN. INFO.:			US 2002-418803P	P 20021016 <--
			WO 2003-US32667	W 20031016 <--
ED	Entered STN: 18 Feb 2005			
AB	The invention provides methods and compns. for modulating the sensitivity of cells to cytotoxic compds. and other active agents. In accordance with the invention, compns. are provided comprising combinations of ectophosphatase inhibitors and active agents. Active agents include antibiotics, fungicides, herbicides, insecticides, chemotherapeutic agents, and plant growth regulators. By increasing the efficacy of active agents, the invention allows use of compns. with lowered concns. of active ingredients.			
IT	50-00-0, Formaldehyde, biological studies 2440-22-4 18249-20-2 26027-38-3 51609-41-7 53404-04-9 70024-53-2 856668-65-0 RL: PAC (Pharmacological activity); THU (Therapeutic use); BIOL (Biological study); USES (Uses) (methods and compns. for increasing efficacy of biol. active ingredients such as antitumor agents)			
RN	50-00-0 HCAPLUS			
CN	Formaldehyde (CA INDEX NAME)			

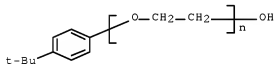
RN 2440-22-4 HCAPLUS

CN Phenol, 2-(2H-benzotriazol-2-yl)-4-methyl- (CA INDEX NAME)



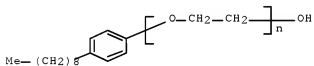
RN 18249-20-2 HCAPLUS

CN Poly(oxy-1,2-ethanediyl), α -(4-(1,1-dimethylethyl)phenyl)- ω -hydroxy- (CA INDEX NAME)



RN 26027-38-3 HCAPLUS

CN Poly(oxy-1,2-ethanediyl), α -(4-nonylphenyl)- ω -hydroxy- (CA INDEX NAME)



RN 51609-41-7 HCAPLUS

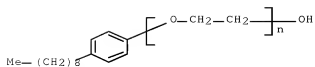
CN Poly(oxy-1,2-ethanediyl), α -(4-nonylphenyl)- ω -hydroxy-, phosphate (CA INDEX NAME)

CM 1

CRN 26027-38-3

CMF (C2 H4 O)_n C15 H24 O

CCI PMS



CM 2

CRN 7664-38-2

CMF H3 O4 P



RN 53404-04-9 HCAPLUS

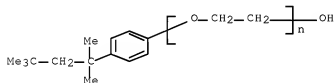
CN Poly(oxy-1,2-ethanediyl), α -[4-(1,1,3,3-tetramethylbutyl)phenyl]-
o-hydroxy-, compd. with iodine (9CI) (CA INDEX NAME)

CM 1

CRN 9002-93-1

CMF (C2 H4 O) $_n$ C14 H22 O

CCI PMS



CM 2

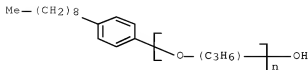
CRN 7553-56-2

CMF I2

I-1

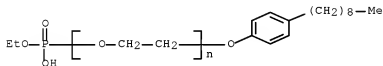
RN 70024-53-2 HCAPLUS

CN Poly[oxy(methyl-1,2-ethanediyl)], α -(4-nonylphenyl)- ω -hydroxy-
(CA INDEX NAME)



RN 856668-65-0 HCAPLUS

CN Poly[oxy-1,2-ethanediyl], α -(ethoxyhydroxyphosphinyl)- ω -(4-nonylphenoxy)-, magnesium salt (2:1) (9CI) (CA INDEX NAME)



● 1/2 Mg

REFERENCE COUNT: 3 THERE ARE 3 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L84 ANSWER 4 OF 16 HCAPLUS COPYRIGHT 2009 ACS on STN
 ACCESSION NUMBER: 2005:13585 HCAPLUS [Full-text](#)
 DOCUMENT NUMBER: 142:76112
 TITLE: Weather-resistant agents and method for treating colored materials with them
 INVENTOR(S): Noborio, Kazuhiko
 PATENT ASSIGNEE(S): Nippon Kayaku Co., Ltd., Japan; NS Color Techno K. K.; Rise Chemical Research Y. K.
 SOURCE: Jpn. Kokai Tokkyo Koho, 18 pp.
 CODEN: JKXXAF
 DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2005002484	A	20050106	JP 2003-164736	20030610 <--
PRIORITY APPLN. INFO.:			JP 2003-164736	20030610 <--

OTHER SOURCE(S): MARPAT 142:76112

ED Entered STN: 07 Jan 2005

AB The agents, useful for natural or synthetic fibers, leather, paper, and rush materials, contain copolymers (A) from ethylenic double bond-containing benzophenone and/or benzotriazole compds. and (meth)acrylic esters and/or hydroxyethyl (meth)acrylate and semicarbazide compds. (B). Thus, immersing a dyed cotton knit in a composition containing a 95:5 mixture of copolymer from Aqualon HS 20 (reactive emulsifier) 15, 2-hydroxy-4-

methacryloyloxyethoxybenzophenone 45, Me methacrylate (I) 30, 2-hydroxyethyl methacrylate (II) 20, and acrylic acid (III) 5 parts and 1,6-hexamethylenedis(N,N-dimethylsemicarbazide) (IV) 35, a 95:5 mixture of Aqualon HS 20-RUVA 93 [2-(2-hydroxy-5-methacryloyloxyphenyl)-2H-benzotriazole]-I-II-III copolymer and IV 35, 5% 2-hydroxymethoxy-5-sulfobenzophenone 15, and 5% 3-[3-tert-butyl-5-(chloro-2H-benzotriazol-2-yl)-4-hydroxyphenyl]propionic acid 15 parts resulted in good discoloration prevention.

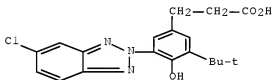
IT 83573-67-5

RL: MOA (Modifier or additive use); TEM (Technical or engineered material use); USES (Uses)

(light stabilizer, agent optionally containing; weather-resistant agents containing benzophenone and/or benzotriazole polymers and semicarbazide compds. for dyed fibers, leather, paper, and tatami mat)

RN 83573-67-5 HCAPLUS

CN Benzenepropanoic acid, 3-(5-chloro-2H-benzotriazol-2-yl)-5-(1,1-dimethylethyl)-4-hydroxy- (CA INDEX NAME)



IT 812665-09-1P, Acrylic acid-Aqualon HS 20-2-hydroxyethyl methacrylate-2-hydroxy-4-methacryloyloxyethoxybenzophenone-methyl methacrylate copolymer 812665-10-4P

RL: IMF (Industrial manufacture); MOA (Modifier or additive use); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses) (weather-resistant agents containing benzophenone and/or benzotriazole polymers and semicarbazide compds. for dyed fibers, leather, paper, and tatami mat)

RN 812665-09-1 HCAPLUS

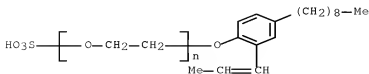
CN 2-Propenoic acid, 2-methyl-, 2-(4-benzoyl-3-hydroxyphenoxy)ethyl ester, polymer with 2-hydroxyethyl 2-methyl-2-propenoate, methyl 2-methyl-2-propenoate, 2-propenoic acid and α-sulfo-ω-[4-nonyl-2-(1-propenyl)phenoxy]poly(oxy-1,2-ethanediyl) ammonium salt, graft (9CI) (CA INDEX NAME)

CM 1

CRN 140651-97-4

CMF (C2 H4 O)n C18 H28 O4 S . H3 N

CCI PMS

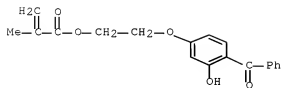


● NH₃

CM 2

CRN 16613-04-0

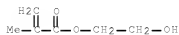
CMF C19 H18 O5



CM 3

CRN 868-77-9

CMF C6 H10 O3



CM 4

CRN 80-62-6

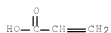
CMF C5 H8 O2



CM 5

CRN 79-10-7

CMF C3 H4 O2



RN 812665-10-4 HCAPLUS

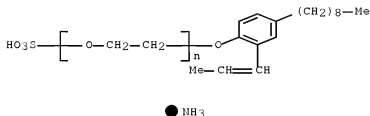
CN 2-Propenoic acid, 2-methyl-, 2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl ester, polymer with 2-hydroxyethyl 2-methyl-2-propenoate, methyl 2-methyl-2-propenoate, 2-propenoic acid and α -sulfo- ω -(4-nonyl-2-(1-propenyl)phenoxy)poly(oxy-1,2-ethanediyl) ammonium salt, graft (9CI) (CA INDEX NAME)

CM 1

CRN 140651-97-4

CMF (C2 H4 O)_n C18 H28 O4 S . H3 N

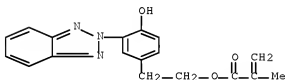
CCI PMS



CM 2

CRN 96478-09-0

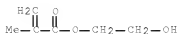
CMF C18 H17 N3 O3



CM 3

CRN 868-77-9

CMF C6 H10 O3



CM 4

CRN 80-62-6

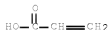
CMF C5 H8 O2



CM 5

CRN 79-10-7

CMF C3 H4 O2



L84 ANSWER 5 OF 16 HCAPLUS COPYRIGHT 2009 ACS on STN

ACCESSION NUMBER: 2004:872823 HCAPLUS Full-text

DOCUMENT NUMBER: 141:366906

TITLE: Light stabilizing polymer dispersants in pigment dispersions

INVENTOR(S): Vogel, Thomas; Soder, Sibylle; Simmendinger, Peter

PATENT ASSIGNEE(S): Ciba Specialty Chemicals Holding Inc., Switz.

SOURCE: PCT Int. Appl., 96 pp.

CODEN: PIXXD2

DOCUMENT TYPE: Patent

LANGUAGE: English

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
WO 2004090030	A1	20041021	WO 2004-EP50386	20040329 <--
W: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BW, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, EG, ES, FI, GB, GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NA, NI, NO, NZ, OM, PG, PH, PL, PT, RO, RU, SC, SD, SE, SG, SK, SL, SY, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, YU, ZA, ZM, ZW				
RW: BW, GH, GM, KE, LS, MW, MZ, SD, SL, SZ, TZ, UG, ZM, ZW, AM, AZ, BY, KG, KZ, MD, RU, TJ, TM, AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HU, IE, IT, LU, MC, NL, PL, PT, RO, SE, SI, SK, TR, BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG				
AU 2004228365	A1	20041021	AU 2004-228365	20040329 <--
CA 2520066	A1	20041021	CA 2004-2520066	20040329 <--
EP 1611197	A1	20060104	EP 2004-724025	20040329 <--
R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, HU, PL, SK				
CN 1802409	A	20060712	CN 2004-80009361	20040329 <--
JP 2006526670	T	20061124	JP 2006-505501	20040329 <--
US 20060229407	A1	20061012	US 2005-551978	20051005 <--
IN 2005CN02904	A	20070302	IN 2005-CN2904	20051107 <--
PRIORITY APPLN. INFO.:			EP 2003-405235	A 20030408 <--

OTHER SOURCE(S):

MARPAT 141:366906

ED Entered STN: 21 Oct 2004

AB Polymers based on esters of unsatd. acids and having light-protecting groups attached to the chains are manufactured by atom-transfer radical polymerization and are useful for dispersants of pigments in compns. based on materials susceptible to degradation by light, heat, and oxidation so as to prevent this degradation. A typical polymer was manufactured by polymerization of Bu methacrylate in the presence of CuCl, pentamethyldiethylenetriamine (I), and p-toluenesulfonic acid, polymerization of glycidyl methacrylate in the presence of the resulting polymer, I, and CuCl, and reaction of the resulting block copolymer with 2,4-bis[4-(1,1'-biphenyl)]-6-(2,4-dihydroxyphenyl)triazine.

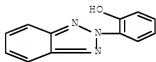
IT 10096-91-0DP, 2-(2-Hydroxyphenyl)benzotriazole, reaction products with polymers 776323-55-8P 776323-58-1P 778595-77-0P

RL: IMF (Industrial manufacture); MOA (Modifier or additive use); PREP (Preparation); USES (Uses)

(light-stabilizing polymer dispersants for pigments in compns. based on polymers susceptible to light degradation)

RN 10096-91-0 HCAPLUS

CN Phenol, 2-(2H-benzotriazol-2-yl)- (CA INDEX NAME)



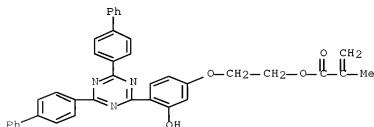
RN 776323-55-8 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 2-[4-[4,6-bis([1,1'-biphenyl]-4-yl)-1,3,5-triazin-2-yl]-3-hydroxyphenoxy]ethyl ester, polymer with butyl 2-methyl-2-propenoate, diblock (9CI) (CA INDEX NAME)

CM 1

CRN 776323-54-7

CMF C39 H31 N3 O4



CM 2

CRN 97-88-1

CMF C8 H14 O2



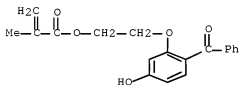
RN 776323-58-1 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 2-(2-benzoyl-5-hydroxyphenoxy)ethyl ester, polymer with butyl 2-methyl-2-propenoate, diblock (9CI) (CA INDEX NAME)

CM 1

CRN 776323-57-0

CMF C19 H18 O5



CM 2

CRN 97-88-1

CMF C8 H14 O2



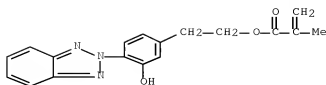
RN 778595-77-0 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 2-[4-(2H-benzotriazol-2-yl)-3-hydroxyphenyl]ethyl ester, polymer with butyl 2-methyl-2-propenoate, diblock (9CI) (CA INDEX NAME)

CM 1

CRN 161538-31-4

CMF C18 H17 N3 O3



CM 2

CRN 97-88-1

CMF C8 H14 O2



REFERENCE COUNT: 4 THERE ARE 4 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L84 ANSWER 6 OF 16 HCAPLUS COPYRIGHT 2009 ACS on STN
 ACCESSION NUMBER: 2004:433778 HCAPLUS Full-text
 DOCUMENT NUMBER: 141:8720
 TITLE: Polymeric dispersants to improve smear in printing
 INVENTOR(S): Sacoto, Paul; Sun, Jing X.; Sun, Naiyu
 PATENT ASSIGNEE(S): Lexmark International, Inc., USA
 SOURCE: U.S. Pat. Appl. Publ., 13 pp.
 CODEN: USXXCO
 DOCUMENT TYPE: Patent
 LANGUAGE: English
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
US 20040102541	A1	20040527	US 2002-304592	20021126 <--
US 6984701	B2	20060110		
WO 2005118716	A1	20051215	WO 2004-US16332	20040525 <--
W: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BW, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, EG, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NA, NI, NO, NZ, OM, PG, PH, PL, PT, RO, RU, SC, SD, SE, SG, SK, SL, SY, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, YU, ZA, ZM, ZW RW: BW, GH, GM, KE, LS, MW, MZ, NA, SD, SL, SZ, TZ, UG, ZM, ZW, AM, AZ, BY, KG, KZ, MD, RU, TJ, TM, AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HU, IE, IT, LU, MC, NL, PL, PT, RO, SE, SI, SK, TR, BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG				
AU 2004320023	A1	20060119	AU 2004-320023	20040525 <--
BR 2004011516	A	20060801	BR 2004-11516	20040525 <--
CN 1863865	A	20061115	CN 2004-80019887	20040525 <--
EP 1753816	A1	20070221	EP 2004-753204	20040525 <--

R: DE, FR, GB
 PRIORITY APPLN. INFO.:

US 2002-304592
 WO 2004-US16332

A 20021126 <--
 A 20040525 <--

ED Entered STN: 28 May 2004

AB This invention relates to polymeric dispersants useful in ink jet ink compns. The graft polymers comprise monomers having electron rich functional groups, which exhibit favorable interactions with the surface of pigment particles thereby better stabilizing the pigment dispersion within the aqueous ink composition. The graft polymers also comprise hydrophobic monomers having the ability to form hydrogen bonding. The polymers of the present invention provide a dispersant that increases the smear resistance of pigmented inks, especially when used on photo or gelatin paper. The graft polymers also provide excellent chroma for printing. The present invention also relates to aqueous ink compns. which include those polymeric dispersants. Thus, methacrylic acid 24.0, 2-hydroxyethyl methacrylate 20.0, and polypropylene glycol 4-nonylphenyl ether acrylate 45.0 g were polymerized to give a graft copolymer dispersant with Mw 8211 and Mn 4523, 20% KOH was added therein and mixed with a pigment (dispersant: pigment = 1:1), maintained pH at 7.5 using 20% KOH, and diluted to give a 12-15%-solids premix, the resulting premix was mixed with pigment 3, 2-pyrrolidone 5, polyethylene glycol 5, thiodiethanol 5, and 1,2-hexanediol 1%, and water to give an ink composition showing good smear resistance and water fastness property.

IT 693813-90-0P 693813-93-3P 693813-96-6P
 693813-99-9P 693814-02-7P 694439-33-3P,
 Ethylene oxide-2-(2'-hydroxy-5'-methacryloxyethylphenyl)-2H-benzotriazole-methacrylic acid graft copolymer 2,4,6-tris(1-phenylethyl)phenyl ether potassium salt 694439-35-5P, Ethylene oxide-2-hydroxyethyl methacrylate-2-(2'-hydroxy-5'-methacryloxyethylphenyl)-2H-benzotriazole-methacrylic acid graft copolymer 2,4,6-tris(1-phenylethyl)phenyl ether potassium salt

RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)

(preparation of polymeric dispersants to improve smear in printing)

RN 693813-90-0 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, polymer with 2-hydroxyethyl 2-methyl-2-propenoate and α -(1-oxo-2-propenyl)- ω -(4-nonylphenoxy)poly[oxy(methyl-1,2-ethanediyl)], graft, potassium salt (9CI)
 (CA INDEX NAME)

CM 1

CRN 693813-89-7

CMF (C6 H10 O3 . C4 H6 O2 . (C3 H6 O)_n C18 H26 O2)_x

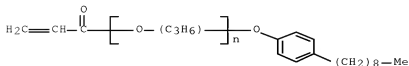
CCI PMS

CM 2

CRN 72246-47-0

CMF (C3 H6 O)_n C18 H26 O2

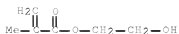
CCI IDS, PMS



CM 3

CRN 868-77-9

CMF C6 H10 O3



CM 4

CRN 79-41-4

CMF C4 H6 O2



RN 693813-93-3 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, polymer with 2-hydroxyethyl
 2-methyl-2-propenoate, α -(2-methyl-1-oxo-2-propenyl)- ω -[2,4,6-
 tris(1-phenylethyl)phenoxy]poly(oxy-1,2-ethanediyl) and
 α -(1-oxo-2-propenyl)- ω -(4-nonylphenoxy)poly[oxy(methyl-1,2-
 ethanediyl)], graft, potassium salt (9CI) (CA INDEX NAME)

CM 1

CRN 693813-92-2

CMF (C6 H10 O3 . C4 H6 O2 . (C3 H6 O)n C18 H26 O2 . (C2 H4 O)n C34 H34
 O2)x

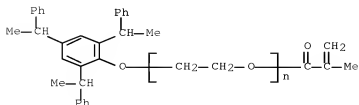
CCI PMS

CM 2

CRN 174200-85-2

CMF (C2 H4 O)n C34 H34 O2

CCI PMS

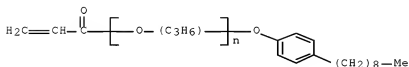


CM 3

CRN 72246-47-0

CMF (C3 H6 O)_n C18 H26 O2

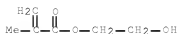
CCI IDS, PMS



CM 4

CRN 868-77-9

CMF C6 H10 O3



CM 5

CRN 79-41-4

CMF C4 H6 O2



RN 693813-96-6 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, polymer with 2-hydroxyethyl 2-methyl-2-propenoate and α -(2-methyl-1-oxo-2-propenyl)- ω -[2,4,6-tris(1-phenylethyl)phenoxy]poly(oxy-1,2-ethanediyl), graft, potassium salt (9CI) (CA INDEX NAME)

CM 1

CRN 693813-95-5

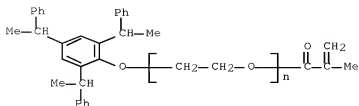
CMF (C6 H10 O3 . C4 H6 O2 . (C2 H4 O)_n C34 H34 O2)_x

CCI PMS

CM 2

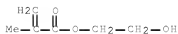
CRN 174200-85-2

CMF (C2 H4 O)_n C34 H34 O2
 CCI PMS



CM 3

CRN 868-77-9
 CMF C6 H10 O3



CM 4

CRN 79-41-4
 CMF C4 H6 O2



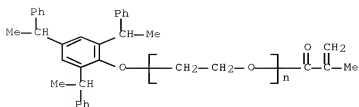
RN 693813-99-9 HCAPLUS
 CN 2-Propenoic acid, 2-methyl-, polymer with
 2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl 2-methyl-2-propenoate
 and α -(2-methyl-1-oxo-2-propenyl)- ω -[2,4,6-tris(1-phenylethyl)phenoxy]poly(oxy-1,2-ethanediyl), graft, potassium salt (9CI)
 (CA INDEX NAME)

CM 1

CRN 693813-98-8
 CMF (C18 H17 N3 O3 . C4 H6 O2 . (C2 H4 O)_n C34 H34 O2)_x
 CCI PMS

CM 2

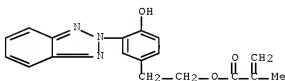
CRN 174200-85-2
 CMF (C2 H4 O)_n C34 H34 O2
 CCI PMS



CM 3

CRN 96478-09-0

CMF C18 H17 N3 O3



CM 4

CRN 79-41-4

CMF C4 H6 O2



RN 693814-02-7 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, polymer with
 2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl 2-methyl-2-propenoate,
 2-hydroxyethyl 2-methyl-2-propenoate and
 α -(2-methyl-1-oxo-2-propenyl)- ω -[2,4,6-tris(1-phenylethyl)phenoxy]poly(oxy-1,2-ethanediyl), graft, potassium salt (9CI)
 (CA INDEX NAME)

CM 1

CRN 693814-01-6

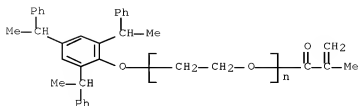
CMF (C18 H17 N3 O3 . C6 H10 O3 . C4 H6 O2 . (C2 H4 O)n C34 H34 O2)x

CCI PMS

CM 2

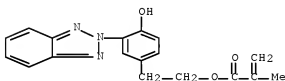
CRN 174200-85-2

CMF (C2 H4 O)n C34 H34 O2
CCI PMS



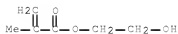
CM 3

CRN 96478-09-0
CMF C18 H17 N3 O3



CM 4

CRN 868-77-9
CMF C6 H10 O3



CM 5

CRN 79-41-4
CMF C4 H6 O2



RN 694439-33-3 HCAPLUS
CN 2-Propenoic acid, 2-methyl-, polymer with

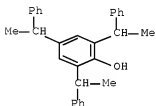
Serial No.:10/582,307

2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl 2-methyl-2-propenoate
and oxirane, 2,4,6-tris(1-phenylethyl)phenyl ether, graft, potassium salt
(9CI) (CA INDEX NAME)

CM 1

CRN 18254-13-2

CMF C30 H30 O



CM 2

CRN 694439-32-2

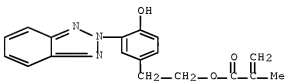
CMF (C18 H17 N3 O3 . C4 H6 O2 . C2 H4 O) x

CCI PMS

CM 3

CRN 96478-09-0

CMF C18 H17 N3 O3



CM 4

CRN 79-41-4

CMF C4 H6 O2



CM 5

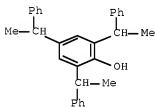
CRN 75-21-8
CMF C2 H4 O



RN 694439-35-5 HCAPLUS
CN 2-Propenoic acid, 2-methyl-, polymer with
2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl 2-methyl-2-propenoate,
2-hydroxyethyl 2-methyl-2-propenoate and oxirane,
2,4,6-tris(1-phenylethyl)phenyl ether, graft, potassium salt (9CI) (CA
INDEX NAME)

CM 1

CRN 18254-13-2
CMF C30 H30 O

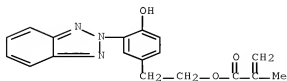


CM 2

CRN 694439-34-4
CMF (C18 H17 N3 O3 . C6 H10 O3 . C4 H6 O2 . C2 H4 O)x
CCI PMS

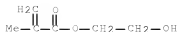
CM 3

CRN 96478-09-0
CMF C18 H17 N3 O3



CM 4

CRN 868-77-9
CMF C6 H10 O3



CM 5

CRN 79-41-4
CMF C4 H6 O2



CM 6

CRN 75-21-8
CMF C2 H4 O



REFERENCE COUNT: 12 THERE ARE 12 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L84 ANSWER 7 OF 16 HCAPLUS COPYRIGHT 2009 ACS on STN
 ACCESSION NUMBER: 2003:771639 HCAPLUS Full-text
 DOCUMENT NUMBER: 139:293337
 TITLE: Thermally insulating linings
 INVENTOR(S): Saegusa, Koichi; Horiike, Taizo; Kubo, Kenzo
 PATENT ASSIGNEE(S): Toray Industries, Inc., Japan
 SOURCE: Jpn. Kokai Tokkyo Koho, 9 pp.
 CODEN: JKXXAF
 DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
-----	---	-----	-----	-----
JP 2003278017	A	20031002	JP 2002-80270	20020322 <--
PRIORITY APPLN. INFO.:			JP 2002-80270	20020322 <--
OTHER SOURCE(S):	MARPAT	139:293337		
ED Entered STN:	02 Oct 2003			

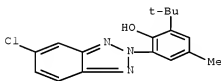
AB Linings are prepared from fibers containing 3-60% poly(phenylene sulfides) (I) and ≥ 1 fiber selected from cotton, wool, polyacrylonitrile, polyester, and polyamide fibers. Thus, a lining was prepared from 60% long fibers of I impregnated with 2-(2'-hydroxy-3'-tert-butyl-5'-methylphenyl)-5-chlorobenzotriazole and 40% 70-30 acrylic-wool.

IT 3896-11-5, 2-(2'-Hydroxy-3'-tert-butyl-5'-methylphenyl)-5-chlorobenzotriazole 9004-78-8D, Polyethylene glycol phenyl ether, styrenated

RL: MOA (Modifier or additive use); USES (Uses)
(thermally insulating linings containing poly(phenylene sulfide) fibers and other fibers)

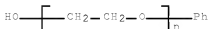
RN 3896-11-5 HCAPLUS

CN Phenol, 2-(5-chloro-2H-benzotriazol-2-yl)-6-(1,1-dimethylethyl)-4-methyl- (CA INDEX NAME)



RN 9004-78-8 HCAPLUS

CN Poly(oxy-1,2-ethanediyl), α -phenyl- ω -hydroxy- (CA INDEX NAME)



L84 ANSWER 8 OF 16 HCAPLUS COPYRIGHT 2009 ACS on STN

ACCESSION NUMBER: 2003:711699 HCAPLUS Full-text

DOCUMENT NUMBER: 139:246970

TITLE: Ultraviolet ray absorbents and polymer-bond benzotriazole ultraviolet ray absorbents and manufacture methods and treated articles and treating methods

INVENTOR(S): Shimanaka, Hiroyuki; Saikatsu, Hiroaki; Fukuda, Tetsuo; Yamashita, Rokuya; Nakamura, Michie

PATENT ASSIGNEE(S): Dainichiseika Color and Chemical Mfg. Co., Ltd., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 21 pp.
CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

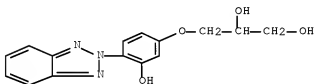
FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

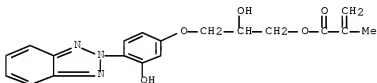
PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2003253248	A	20030910	JP 2002-56283	20020301 <--
JP 2007169660	A	20070705	JP 2007-67200	20070315 <--
PRIORITY APPLN. INFO.:			JP 2002-56283	A3 20020301 <--

ED Entered STN: 11 Sep 2003

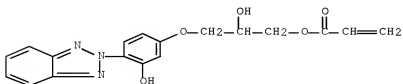
- AB 2-(2',4'-Dihydroxyphenyl)-2H-benzotriazole (I) is treated with epoxides or alc. OH group-containing halogen compds. to prepare reactive UV absorbers. Thus, I was treated with 4-chloro-1-butanol to prepare 2-benzotriazole-2-yl-5-(4'-hydroxybutoxy)phenol, which (70.8 parts) was treated with 100 parts 25:75 Et acrylate-ethylene copolymer to prepare a polymer-bond UV absorber.
- IT 5538-26-1P 24802-38-8P 25177-21-3P
 596851-33-1P 596851-35-3P 596851-36-4P
 596851-37-5P 596851-38-6P 596851-39-7P
 RL: IMF (Industrial manufacture); RCT (Reactant); TEM (Technical or engineered material use); PREP (Preparation); RACT (Reactant or reagent); USES (Uses)
 (polymer-bond benzotriazole UV absorbents for inks and coatings and cosmetics and photog. materials)
- RN 5538-26-1 HCAPLUS
- CN 1,2-Propanediol, 3-[4-(2H-benzotriazol-2-yl)-3-hydroxyphenoxy]- (CA INDEX NAME)



- RN 24802-38-8 HCAPLUS
- CN 2-Propenoic acid, 2-methyl-, 3-[4-(2H-benzotriazol-2-yl)-3-hydroxyphenoxy]-2-hydroxypropyl ester (CA INDEX NAME)

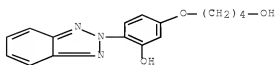


- RN 25177-21-3 HCAPLUS
- CN 2-Propenoic acid, 3-[4-(2H-benzotriazol-2-yl)-3-hydroxyphenoxy]-2-hydroxypropyl ester (CA INDEX NAME)



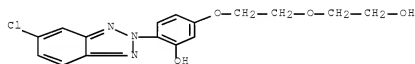
- RN 596851-33-1 HCAPLUS

CN Phenol, 2-(2H-benzotriazol-2-yl)-5-(4-hydroxybutoxy)- (CA INDEX NAME)



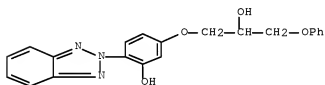
RN 596851-35-3 HCAPLUS

CN Phenol, 2-(5-chloro-2H-benzotriazol-2-yl)-5-[2-(2-hydroxyethoxy)ethoxy]- (CA INDEX NAME)



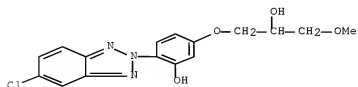
RN 596851-36-4 HCAPLUS

CN Phenol, 2-(2H-benzotriazol-2-yl)-5-(2-hydroxy-3-phenoxypropoxy)- (CA INDEX NAME)



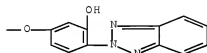
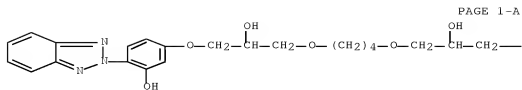
RN 596851-37-5 HCAPLUS

CN Phenol, 2-(5-chloro-2H-benzotriazol-2-yl)-5-(2-hydroxy-3-methoxypropoxy)- (CA INDEX NAME)

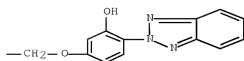
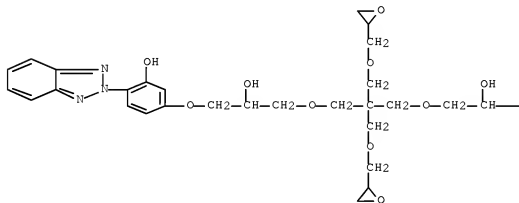


RN 596851-38-6 HCAPLUS

CN Phenol, 3,3'-[1,4-butanediylbis[oxy(2-hydroxy-3,1-propanediyl)oxy]]bis[6-(2H-benzotriazol-2-yl)- (9CI) (CA INDEX NAME)



RN 596851-39-7 HCAPLUS
 CN Phenol, 3,3'-[2,2-bis[oxiranylmethoxy)methyl]-1,3-propanediyl]bis[oxy(2-hydroxy-3,1-propanediyl)oxy]]bis[6-(2H-benzotriazol-2-yl)- (9CI) (CA
 INDEX NAME)



IT 111236--05-6P 596851-34-2P 596851-40-0P
 596851-41-1P 596851-43-3P 596851-44-4P
 596851-45-5P

RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
 (polymer-bond benzotriazole UV absorbents for inks and coatings and cosmetics and photog. materials)

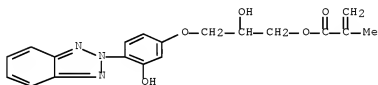
RN 111236-05-6 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 3-[4-(2H-benzotriazol-2-yl)-3-hydroxyphenoxy]-2-hydroxypropyl ester, polymer with ethenylbenzene (9CI) (CA INDEX NAME)

CM 1

CRN 24802-38-8

CMF C19 H19 N3 O5



CM 2

CRN 100-42-5

CMF C8 H8

H₂C=CH-Ph

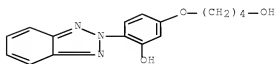
RN 596851-34-2 HCAPLUS

CN 2-Propenoic acid, ethyl ester, polymer with
 2-(2H-benzotriazol-2-yl)-5-(4-hydroxybutoxy)phenol and ethene (9CI) (CA INDEX NAME)

CM 1

CRN 596851-33-1

CMF C16 H17 N3 O3



CM 2

CRN 140-88-5

CMF C5 H8 O2



CM 3

CRN 74-85-1

CMF C2 H4



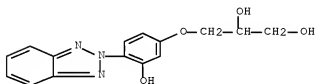
RN 596851-40-0 HCAPLUS

CN 1,4-Benzenedicarboxylic acid, dimethyl ester, polymer with
3-[4-(2H-benzotriazol-2-yl)-3-hydroxyphenoxy]-1,2-propanediol and
1,4-butanediol (9CI) (CA INDEX NAME)

CM 1

CRN 5538-26-1

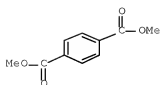
CMF C15 H15 N3 O4



CM 2

CRN 120-61-6

CMF C10 H10 O4



CM 3

CRN 110-63-4

CMF C4 H10 O2



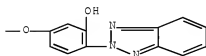
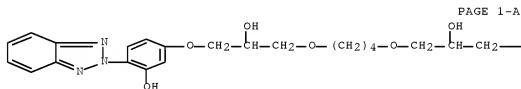
RN 596851-41-1 HCAPLUS

CN 1,4-Benzenedicarboxylic acid, dimethyl ester, polymer with 1,4-butanediol and 3,3'-[1,4-butanediylbis[oxy(2-hydroxy-3,1-propanediyl)oxy]]bis[6-(2H-benzotriazol-2-yl)phenol] (9CI) (CA INDEX NAME)

CM 1

CRN 596851-38-6

CMF C34 H36 N6 O8

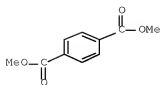


PAGE 1-B

CM 2

CRN 120-61-6

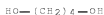
CMF C10 H10 O4



CM 3

CRN 110-63-4

CMF C4 H10 O2



RN 596851-43-3 HCAPLUS

CN Propanoic acid, 3-hydroxy-2-(hydroxymethyl)-2-methyl-, polymer with
 5-amino-1,3,3-trimethylcyclohexanemethanamine,
 3-[4-(2H-benzotriazol-2-yl)-3-hydroxyphenoxy]-1,2-propanediol,
 α -hydro- ω -hydroxypoly(oxy-1,4-butanediyl) and
 5-isocyanato-1-(isocyanatomethyl)-1,3,3-trimethylcyclohexane, ammonium
 salt (9CI) (CA INDEX NAME)

CM 1

CRN 596851-42-2

CMF (C15 H15 N3 O4 . C12 H18 N2 O2 . C10 H22 N2 . C5 H10 O4 . (C4 H8 O)_n
 H2 O)_x

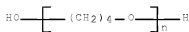
CCI PMS

CM 2

CRN 25190-06-1

CMF (C4 H8 O)_n H2 O

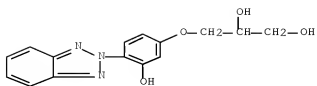
CCI PMS



CM 3

CRN 5538-26-1

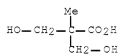
CMF C15 H15 N3 O4



CM 4

CRN 4767-03-7

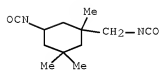
CMF C5 H10 O4



CM 5

CRN 4098-71-9

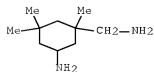
CMF C12 H18 N2 O2



CM 6

CRN 2855-13-2

CMF C10 H22 N2



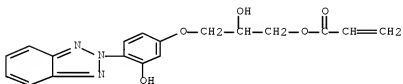
RN 596851-44-4 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, butyl ester, polymer with ethyl
2-methyl-2-propenoate, 2-hydroxyethyl 2-methyl-2-propenoate and
2-hydroxy-3-[3-hydroxy-4-(2H-benzotriazol-2-yl)phenoxy]propyl 2-propenoate
(9CI) (CA INDEX NAME)

CM 1

CRN 25177-21-3

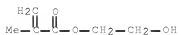
CMF C18 H17 N3 O5



CM 2

CRN 868-77-9

CMF C6 H10 O3



CM 3

CRN 97-88-1

CMF C8 H14 O2



CM 4

CRN 97-63-2

CMF C6 H10 O2



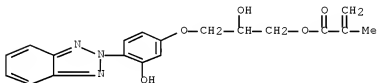
RN 596851-45-5 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 3-[4-(2H-benzotriazol-2-yl)-3-hydroxyphenoxy]-
 2-hydroxypropyl ester, polymer with butyl 2-propenoate, ethyl
 2-methyl-2-propenoate and 2-hydroxyethyl 2-methyl-2-propenoate (9CI) (CA
 INDEX NAME)

CM 1

CRN 24802-38-8

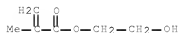
CMF C19 H19 N3 O5



CM 2

CRN 868-77-9

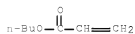
CMF C6 H10 O3



CM 3

CRN 141-32-2

CMF C7 H12 O2



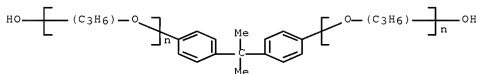
CM 4

CRN 97-63-2

CMF C6 H10 O2

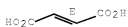


IT 39382-25-7
 RL: POF (Polymer in formulation); TEM (Technical or engineered material use); USES (Uses)
 (polymer-bond benzotriazole UV absorbents for inks and coatings and cosmetics and photog. materials)
 RN 39382-25-7 HCAPLUS
 CN 2-Butenedioic acid (2E)-, polymer with
 α, α' -[(1-methylethylidene)di-4,1-phenylene]bis[ω -hydroxypoly[oxy(methyl-1,2-ethanediyl)]] (CA INDEX NAME)
 CM 1
 CRN 37353-75-6
 CMF (C3 H6 O)n (C3 H6 O)n C15 H16 O2
 CCI IDS, PMS

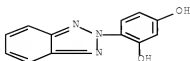


CM 2
 CRN 110-17-8
 CMF C4 H4 O4

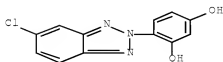
Double bond geometry as shown.



IT 22607-31-4, 2-(2,4-Dihydroxyphenyl)-2H-benzotriazole
 57567-95-0
 RL: RCT (Reactant); RACT (Reactant or reagent)
 (polymer-bond benzotriazole UV absorbents for inks and coatings and cosmetics and photog. materials)
 RN 22607-31-4 HCAPLUS
 CN 1,3-Benzenediol, 4-(2H-benzotriazol-2-yl)- (CA INDEX NAME)



RN 57567-95-0 HCAPLUS
 CN 1,3-Benzenediol, 4-(5-chloro-2H-benzotriazol-2-yl)- (CA INDEX NAME)



L84 ANSWER 9 OF 16 HCAPLUS COPYRIGHT 2009 ACS on STN
 ACCESSION NUMBER: 2003:520420 HCAPLUS Full-text
 DOCUMENT NUMBER: 139:86337
 TITLE: Antisoiling, weather-resistant waterproof sheets
 INVENTOR(S): Suzuki, Kenji
 PATENT ASSIGNEE(S): Hiraoka and Co., Ltd., Japan
 SOURCE: Jpn. Kokai Tokkyo Koho, 28 pp.
 CODEN: JKXXAF
 DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2003191386	A	20030708	JP 2002-93052	20020328 <--
PRIORITY APPLN. INFO.:			JP 2001-95879	A 20010329 <--
			JP 2001-318365	A 20011016 <--

ED Entered STN: 09 Jul 2003

AB The sheets, useful for medium to large-scale tents, etc., consist of a base sheet comprising a base fabric and polymer layer(s) containing natural rubber, synthetic rubber, and/or synthetic resins formed on at least one side of the base fabric, and hydrophilic coating layer(s) containing organosilicates and/or their condensates formed on the polymer layer(s). Thus, a polyester fabric was coated with a composition containing self-emulsifiable acrylic resin (Nipol SX 1706) 70, primary amino group-containing acrylic resin (Polyment NK-CK 200) 30, light stabilizer (Tinofast RSC) 0.2, UV absorber (Tinuvin 213) 0.2, TiO₂ 3, and 5-chlorobenzotriazole 0.1 part on the both sides and dried to give a base sheet, which was coated with an aqueous MeOH solution of Me silicate partial hydrolytic condensation product (MKC Silicate MS 56) 100, γ-glycidioxypropyltrimethoxysilane 10, and organometallic chelating agent 0.3 part on the both sides and dried to give a product showing long-lasting antisoiling properties during outdoor exposure.

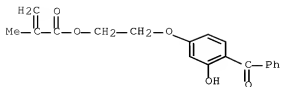
IT 25189-68-8, 2-Hydroxy-4-(methacryloyloxyethoxy)benzophenone-methyl methacrylate copolymer
 RL: POF (Polymer in formulation); PRP (Properties); TEM (Technical or engineered material use); USES (Uses)

(additive migration-proofing layer, ULI 635L; antisoiling, weather-resistant waterproof sheets coated with silicates)

RN 25189-68-8 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 2-(4-benzoyl-3-hydroxyphenoxy)ethyl ester, polymer with methyl 2-methyl-2-propenoate (CA INDEX NAME)

CRN 16613-04-0
CMF C19 H18 O5



CM 2

CRN 80-62-6
CMF C5 H8 O2



IT 25068-38-6, Epikote 828 153175-43-0, Puva 30M
RL: POF (Polymer in formulation); PRP (Properties); TEM (Technical or engineered material use); USES (Uses)
(additive migration-proofing layer; antisoiling, weather-resistant waterproof sheets coated with silicates)
RN 25068-38-6 HCAPLUS
CN Phenol, 4,4'-(1-methylethylidene)bis-, polymer with 2-(chloromethyl)oxirane (CA INDEX NAME)

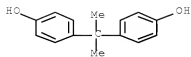
CM 1

CRN 106-89-8
CMF C3 H5 Cl O



CM 2

CRN 80-05-7
CMF C15 H16 O2



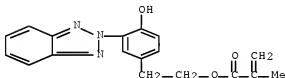
RN 153175-43-0 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl ester, polymer with methyl 2-methyl-2-propenoate (CA INDEX NAME)

CM 1

CRN 96478-09-0

CMF C18 H17 N3 O3



CM 2

CRN 80-62-6

CMF C5 H8 O2



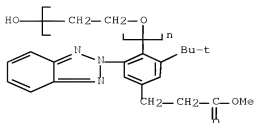
IT 136457-10-8, Tinuvin 213

RL: MOA (Modifier or additive use); USES (Uses)

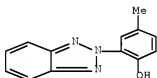
(base fabric coating containing; antisoiling, weather-resistant waterproof sheets coated with silicates)

RN 136457-10-8 HCAPLUS

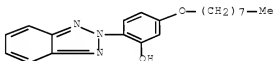
CN Poly(oxy-1,2-ethanediyl), α -[2-(2H-benzotriazol-2-yl)-6-(1,1-dimethylethyl)-4-(3-methoxy-3-oxopropyl)phenyl]- ω -hydroxy- (CA INDEX NAME)



IT 2440-22-4, Tinuvin P 3147-77-1, Viosorb 510
 RL: MOA (Modifier or additive use); USES (Uses)
 (base fabric laminated with film containing; antisoiling, weather-resistant
 waterproof sheets coated with silicates)
 RN 2440-22-4 HCAPLUS
 CN Phenol, 2-(2H-benzotriazol-2-yl)-4-methyl- (CA INDEX NAME)



RN 3147-77-1 HCAPLUS
 CN Phenol, 2-(2H-benzotriazol-2-yl)-5-(octyloxy)- (CA INDEX NAME)



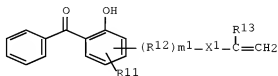
L84 ANSWER 10 OF 16 HCAPLUS COPYRIGHT 2009 ACS on STN
 ACCESSION NUMBER: 2003:110937 HCAPLUS [Full-text](#)
 DOCUMENT NUMBER: 138:154375
 TITLE: Polymeric photostabilizers prepared from reactive UV
 absorbers and reactive hindered amines
 INVENTOR(S): Yamamoto, Ryuichi; Sugimori, Seiji
 PATENT ASSIGNEE(S): Ipposha Oil Industries Co., Ltd., Japan
 SOURCE: Jpn. Kokai Tokkyo Koho, 12 pp.
 CODEN: JKXXAF
 DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2003040937	A	20030213	JP 2001-228438	20010727 <--

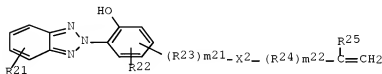
PRIORITY APPLN. INFO.:
 ED Entered STN: 13 Feb 2003
 GI

JP 2001-228438

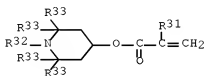
20010727 <--



I



II



III

AB The photostabilizers are copolymers (Mw 1000-1,000,000) of UV-absorbing monomers I [R11 = H, C1-6 alkyl(oxy); R12 = C1-10 (oxy)alkylene; R13 = H, lower alkyl; X1 = ester, amido, ether, or urethane linkage; m1 = 0, 1] and/or II [R21 = H, halo, Me; R22 = H, C1-6 hydrocarbyl; R23 = C1-10 (oxy)alkylene; R24 = (amino or OH group-containing) C1-8 alkylene; R25 = H, lower alkyl; X2 = same as X1; m21, m22 = 0, 1] 15-60, III (R31-R33 = H, lower alkyl) 1-30, vinyl comonomers 30-70, and optionally functional group-bearing vinyl monomers 1-30%. Substrates (e.g., plastics, fibers, paper) are mixed or coated with the photostabilizers to show light resistance for long term. Thus, a dyed acrylic fabric was treated with acrylic acid-ADK Stab LA 82 (1,2,2,6,6-pentamethyl-4-piperidyl methacrylate)-Aqualon HS 20 (reactive emulsifier)-2-hydroxy-4-methacryloyloxybenzophenone-Me methacrylate graft copolymer, showing color fastness grade 5 (JIS L 0804) after 240-h exposure to carbon arc light.

IT 479500-11-3P 479500-12-4P 495400-48-1P
 495400-49-2P 495400-52-7P 495400-55-0P
 495400-58-3P 495400-61-8P 496019-42-2P,
 Acrylic acid-ADK Stab LA 82-ethylene
 oxide-2-hydroxy-4-acryloyloxybenzophenone-2-[2'-hydroxy-5'-
 (methacryloyloxy)phenyl]benzotriazole-methyl methacrylate graft copolymer
 sulfate ammonium salt 496019-43-3P, Acrylic acid-ADK Stab LA
 82-ethylene oxide-2-hydroxy-4-methacryloyloxybenzophenone-2-[2'-hydroxy-5'-
 (methacryloyloxy)phenyl]benzotriazole-methyl acrylate graft copolymer
 sulfate ammonium salt 496019-44-4P, Acrylic acid-ADK Stab LA
 82-butyl methacrylate-ethylene oxide-2-[2'-hydroxy-5'-
 (acryloyloxy)phenyl]benzotriazole graft copolymer sulfate ammonium salt
 RL: IMF (Industrial manufacture); TEM (Technical or engineered material
 use); PREP (Preparation); USES (Uses)
 (polymeric photostabilizers prepared from reactive UV absorbers and
 reactive hindered amines)

RN 479500-11-3 HCAPLUS

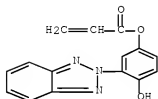
CN 2-Propenoic acid, 2-methyl-, methyl ester, polymer with
 3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl 2-propenoate,

4-benzoyl-3-hydroxyphenyl 2-propenoate and
1,2,2,6,6-pentamethyl-4-piperidiny 2-methyl-2-propenoate (9CI) (CA INDEX
NAME)

CM 1

CRN 158037-94-6

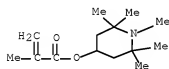
CMF C15 H11 N3 O3



CM 2

CRN 68548-08-3

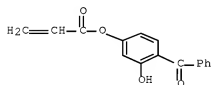
CMF C14 H25 N O2



CM 3

CRN 15419-94-0

CMF C16 H12 O4



CM 4

CRN 80-62-6

CMF C5 H8 O2



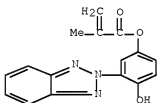
RN 479500-12-4 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl ester, polymer with methyl 2-methyl-2-propenoate and 1,2,2,6,6-pentamethyl-4-piperidiny 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 132288-91-6

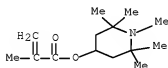
CMF C16 H13 N3 O3



CM 2

CRN 68548-08-3

CMF C14 H25 N O2



CM 3

CRN 80-62-6

CMF C5 H8 O2



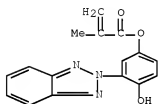
RN 495400-48-1 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl
 ester, polymer with 4-benzoyl-3-hydroxyphenyl 2-propenoate, methyl
 2-methyl-2-propenoate, methyl 2-propenoate and
 1,2,2,6,6-pentamethyl-4-piperidiny 2-methyl-2-propenoate (9CI) (CA INDEX
 NAME)

CM 1

CRN 132288-91-6

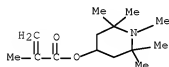
CMF C16 H13 N3 O3



CM 2

CRN 68548-08-3

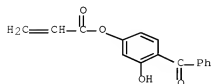
CMF C14 H25 N O2



CM 3

CRN 15419-94-0

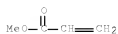
CMF C16 H12 O4



CM 4

CRN 96-33-3

CMF C4 H6 O2



CM 5

CRN 80-62-6

CMF C5 H8 O2



RN 495400-49-2 HCAPLUS

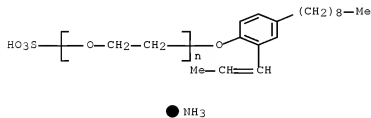
CN 2-Propenoic acid, 2-methyl-, 4-benzoyl-3-hydroxyphenyl ester, polymer with methyl 2-methyl-2-propenoate, 1,2,2,6,6-pentamethyl-4-piperidiny 2-methyl-2-propenoate, 2-propenoic acid and α -sulfo- ω -(4-nonyl-2-(1-propenyl)phenoxy)poly(oxy-1,2-ethanediyl) ammonium salt, graft (9CI) (CA INDEX NAME)

CM 1

CRN 140651-97-4

CMF (C2 H4 O)_n C18 H28 O4 S . H3 N

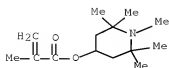
CCI PMS



CM 2

CRN 68548-08-3

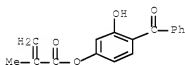
CMF C14 H25 N O2



CM 3

CRN 2035-72-5

CMF C17 H14 O4



CM 4

CRN 80-62-6

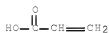
CMF C5 H8 O2



CM 5

CRN 79-10-7

CMF C3 H4 O2

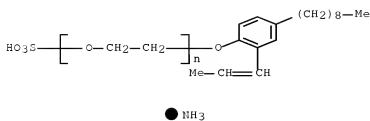


RN 495400-52-7 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 4-benzoyl-3-hydroxyphenyl ester, polymer with ethenylbenzene, 1,2,2,6,6-pentamethyl-4-piperidiny 2-methyl-2-propenoate, 2-propenoic acid and α -sulfo- ω -[4-nonyl-2-(1-propenyl)phenoxy]poly(oxy-1,2-ethanediyl) ammonium salt, graft (9CI) (CA INDEX NAME)

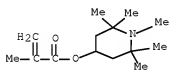
CM 1

CRN 140651-97-4
 CMF (C2 H4 O)_n C18 H28 O4 S . H3 N
 CCI PMS



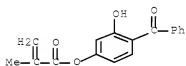
CM 2

CRN 68548-08-3
 CMF C14 H25 N O2



CM 3

CRN 2035-72-5
 CMF C17 H14 O4



CM 4

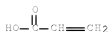
CRN 100-42-5
 CMF C8 H8



CM 5

CRN 79-10-7

CMF C3 H4 O2



RN 495400-55-0 HCAPLUS

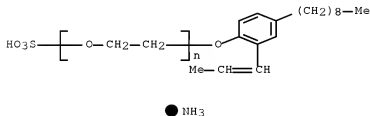
CN 2-Propenoic acid, 2-methyl-, 3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl ester, polymer with 4-benzoyl-3-hydroxyphenyl 2-propenoate, methyl 2-methyl-2-propenoate, 1,2,2,6,6-pentamethyl-4-piperidinyl 2-methyl-2-propenoate, 2-propenoic acid and α -sulfo- ω -(4-nonyl-2-(1-propenyl)phenoxy]poly(oxy-1,2-ethanediyl) ammonium salt, graft (9CI) (CA INDEX NAME)

CM 1

CRN 140651-97-4

CMF (C2 H4 O)_n C18 H28 O4 S . H3 N

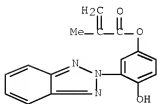
CCI PMS



CM 2

CRN 132288-91-6

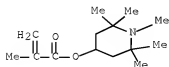
CMF C16 H13 N3 O3



CM 3

CRN 68548-08-3

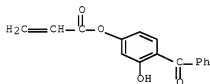
CMF C14 H25 N O2



CM 4

CRN 15419-94-0

CMF C16 H12 O4



CM 5

CRN 80-62-6

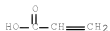
CMF C5 H8 O2



CM 6

CRN 79-10-7

CMF C3 H4 O2



RN 495400-58-3 HCAPLUS

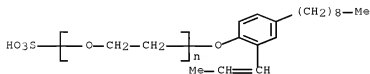
CN 2-Propenoic acid, 2-methyl-, 3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl ester, polymer with 4-benzoyl-3-hydroxyphenyl 2-propenoate, methyl 2-propenoate, 1,2,2,6,6-pentamethyl-4-piperidiny 2-methyl-2-propenoate, 2-propenoic acid and α -sulfo- ω -(4-nonyl-2-(1-propenyl)phenoxy)poly(oxy-1,2-ethanediyl) ammonium salt, graft (9CI) (CA INDEX NAME)

CM 1

CRN 140651-97-4

CMF (C2 H4 O)n C18 H28 O4 S . H3 N

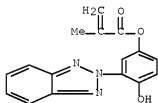
CCI PMS



CM 2

CRN 132288-91-6

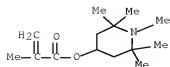
CMF C16 H13 N3 O3



CM 3

CRN 68548-08-3

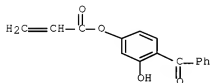
CMF C14 H25 N O2



CM 4

CRN 15419-94-0

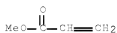
CMF C16 H12 O4



CM 5

CRN 96-33-3

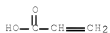
CMF C4 H6 O2



CM 6

CRN 79-10-7

CMF C3 H4 O2



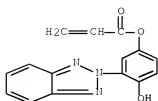
RN 495400-61-8 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, butyl ester, polymer with
 3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl 2-propenoate,
 1,2,2,6,6-pentamethyl-4-piperidiny 2-methyl-2-propenoate, 2-propenoic
 acid and α -sulfo- ω -(4-nonyl-2-(1-propenyl)phenoxy)poly(oxy-1,2-
 ethanediyl) ammonium salt, graft (9CI) (CA INDEX NAME)

CM 1

CRN 158037-94-6

CMF C15 H11 N3 O3

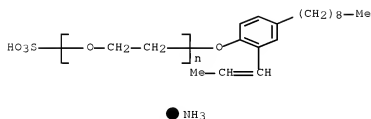


CM 2

CRN 140651-97-4

CMF (C2 H4 O)n C18 H28 O4 S . H3 N

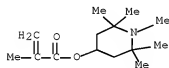
CCI PMS



CM 3

CRN 68548-08-3

CMF C14 H25 N O2



CM 4

CRN 97-88-1

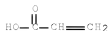
CMF C8 H14 O2



CM 5

CRN 79-10-7

CMF C3 H4 O2



RN 496019-42-2 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl ester, polymer with 4-benzoyl-3-hydroxyphenyl 2-propenoate, methyl 2-methyl-2-propenoate, oxirane, 1,2,2,6,6-pentamethyl-4-piperidinyl 2-methyl-2-propenoate and 2-propenoic acid, hydrogen sulfate (ester), graft, ammonium salt (9CI) (CA INDEX NAME)

CM 1

CRN 7664-93-9

CMF H2 O4 S



CM 2

CRN 495400-56-1

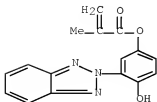
CMF (C16 H13 N3 O3 . C16 H12 O4 . C14 H25 N O2 . C5 H8 O2 . C3 H4 O2 . C2 H4 O)x

CCI PMS

CM 3

CRN 132288-91-6

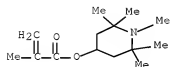
CMF C16 H13 N3 O3



CM 4

CRN 68548-08-3

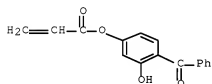
CMF C14 H25 N O2



CM 5

CRN 15419-94-0

CMF C16 H12 O4



CM 6

CRN 80-62-6

CMF C5 H8 O2



CM 7

CRN 79-10-7

CMF C3 H4 O2



CM 8

CRN 75-21-8

CMF C2 H4 O



RN 496019-43-3 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl ester, polymer with 4-benzoyl-3-hydroxyphenyl 2-propenoate, methyl 2-propenoate, oxirane, 1,2,2,6,6-pentamethyl-4-piperidinyl 2-methyl-2-propenoate and 2-propenoic acid, hydrogen sulfate (ester), graft, ammonium salt (9CI) (CA INDEX NAME)

CM 1

CRN 7664-93-9

CMF H2 O4 S



CM 2

CRN 495400-59-4

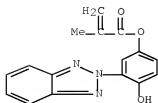
CMF (C16 H13 N3 O3 . C16 H12 O4 . C14 H25 N O2 . C4 H6 O2 . C3 H4 O2 . C2 H4 O)x

CCI PMS

CM 3

CRN 132288-91-6

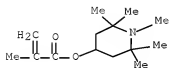
CMF C16 H13 N3 O3



CM 4

CRN 68548-08-3

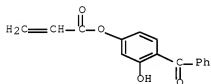
CMF C14 H25 N O2



CM 5

CRN 15419-94-0

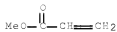
CMF C16 H12 O4



CM 6

CRN 96-33-3

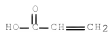
CMF C4 H6 O2



CM 7

CRN 79-10-7

CMF C3 H4 O2



CM 8

CRN 75-21-8

CMF C2 H4 O



RN 496019-44-4 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, butyl ester, polymer with
 3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl 2-propenoate, oxirane,
 1,2,2,6,6-pentamethyl-4-piperidiny 2-methyl-2-propenoate and 2-propenoic
 acid, hydrogen sulfate (ester), graft, ammonium salt (9CI) (CA INDEX
 NAME)

CM 1

CRN 7664-93-9

CMF H2 O4 S



CM 2

CRN 495400-62-9

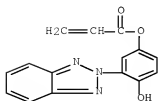
CMF (C15 H11 N3 O3 . C14 H25 N O2 . C8 H14 O2 . C3 H4 O2 . C2 H4 O)x

CCI PMS

CM 3

CRN 158037-94-6

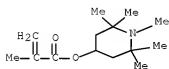
CMF C15 H11 N3 O3



CM 4

CRN 68548-08-3

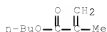
CMF C14 H25 N O2



CM 5

CRN 97-88-1

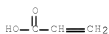
CMF C8 H14 O2



CM 6

CRN 79-10-7

CMF C3 H4 O2



CM 7

CRN 75-21-8

CMF C2 H4 O



Serial No.:10/582,307

DOCUMENT NUMBER: 135:196989
 TITLE: Room-temperature-curable modified silicone sealing compositions with weather resistance
 INVENTOR(S): Mori, Hiroshi
 PATENT ASSIGNEE(S): Ohtsuka Chemical Co., Ltd., Japan
 SOURCE: Jpn. Kokai Tokkyo Koho, 14 pp.
 CODEN: JKXXAF
 DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2001234072	A	20010828	JP 2000-47794	20000224 <--
JP 3280949	B2	20020513		

PRIORITY APPLN. INFO.: JP 2000-47794 20000224 <--
 ED Entered STN: 30 Aug 2001

AB Title compns. contain 100 parts reactive silyl group-containing polyethers, 0.01-20 parts aminosilanes, 2-20 parts polymeric UV absorbers prepared from (meth)acrylic benzotriazoles and/or (meth)acrylic triazines 10-50, reactive silyl-containing vinyl compds. 5-20, (meth)acrylate esters 25-85, and polymerizable hindered amines 0-2%, and 0.01-20 parts Sn catalysts. A composition comprising MS polymer S 203 100, TSL 8340 2, 4:3:3 trimethoxysilylpropyl methacrylate-tris(trimethylsiloxy)silylpropyl methacrylate-RUVA 93 copolymer 2, Tinuvin 123 0.05, a Sn catalyst 2, and additives 135 parts showed maximum tensile stress 72 N/cm2 and elongation 450% initially and 79 and 380, resp. after 2,000 h under dew-cycle weatherometer.

IT 356566-74-0P 356566-75-1P 356566-76-2P
 357166-90-6P 357166-91-7P 357166-92-8P
 357166-93-9P 357166-94-0P
 RL: IMF (Industrial manufacture); POF (Polymer in formulation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses) (room temperature-curable UV absorber-polymerized polyether silicone sealants with weather resistance)

RN 356566-74-0 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl ester, polymer with 2-ethylhexyl 2-methyl-2-propenoate, MS Polymer S 903, N-[3-(trimethoxysilyl)propyl]-1,2-ethanediamine and 3-(trimethoxysilyl)propyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

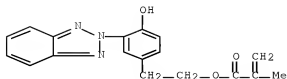
CM 1

CRN 183510-69-2
 CMF Unspecified
 CCI PMS, MAN

*** STRUCTURE DIAGRAM IS NOT AVAILABLE ***

CM 2

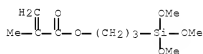
CRN 96478-09-0
 CMF C18 H17 N3 O3



CM 3

CRN 2530-85-0

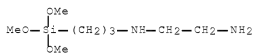
CMF C10 H20 O5 S1



CM 4

CRN 1760-24-3

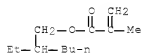
CMF C8 H22 N2 O3 S1



CM 5

CRN 688-84-6

CMF C12 H22 O2



RN 356566-75-1 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl ester, polymer with methyl 2-methyl-2-propenoate, MS Polymer S 903, 1,2,2,6,6-pentamethyl-4-piperidinyl 2-methyl-2-propenoate, N-[3-(trimethoxysilyl)propyl]-1,2-ethanediamine and

3-(trimethoxysilyl)propyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 183510-69-2

CMF Unspecified

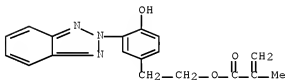
CCI PMS, MAN

*** STRUCTURE DIAGRAM IS NOT AVAILABLE ***

CM 2

CRN 96478-09-0

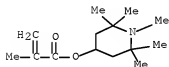
CMF C18 H17 N3 O3



CM 3

CRN 68548-08-3

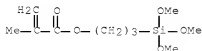
CMF C14 H25 N O2



CM 4

CRN 2530-85-0

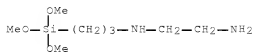
CMF C10 H20 O5 Si



CM 5

CRN 1760-24-3

CMF C8 H22 N2 O3 Si



CM 6

CRN 80-62-6

CMF C5 H8 O2



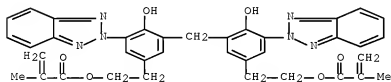
RN 356566-76-2 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, methylenebis[5-(2H-benzotriazol-2-yl)-4-hydroxy-3,1-phenylene]-2,1-ethanediyl] ester, polymer with methyl 2-methyl-2-propenoate, MS Polymer S 903, N-[3-(trimethoxysilyl)propyl]-1,2-ethanediamine and 3-(trimethoxysilyl)propyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 263909-63-3

CMF C37 H34 N6 O6



CM 2

CRN 183510-69-2

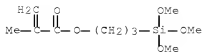
CMF Unspecified

CCI PMS, MAN

*** STRUCTURE DIAGRAM IS NOT AVAILABLE ***

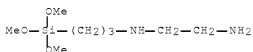
CM 3

CRN 2530-85-0
CMF C10 H20 O5 Si



CM 4

CRN 1760-24-3
CMF C8 H22 N2 O3 Si



CM 5

CRN 80-62-6
CMF C5 H8 O2



RN 357166-90-6 HCAPLUS
CN 2-Propenoic acid, 2-methyl-, 2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl ester, polymer with Kaneka MS Polymer S 203, N-[3-(trimethoxysilyl)propyl]-1,2-ethanediamine, 3-(trimethoxysilyl)propyl 2-methyl-2-propenoate and 3-[3,3,3-trimethyl-1,1-bis[(trimethylsilyl)oxy]disiloxanyl]propyl 2-methyl-2-propenoate (9CI)
(CA INDEX NAME)

CM 1

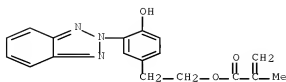
CRN 178535-69-8
CMF Unspecified
CCI PMS, MAN

*** STRUCTURE DIAGRAM IS NOT AVAILABLE ***

CM 2

CRN 96478-09-0

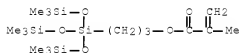
CMF C18 H17 N3 O3



CM 3

CRN 17096-07-0

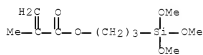
CMF C16 H38 O5 Si4



CM 4

CRN 2530-85-0

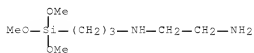
CMF C10 H20 O5 Si



CM 5

CRN 1760-24-3

CMF C8 H22 N2 O3 Si



RN 357166-91-7 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 2-[3-(2H-benzotriazol-2-yl)-4-

hydroxyphenyl]ethyl ester, polymer with Kaneka MS Polymer S 203, methyl 2-methyl-2-propenoate, N-[3-(trimethoxysilyl)propyl]-1,2-ethanediamine and 3-(trimethoxysilyl)propyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 178535-69-8

CMF Unspecified

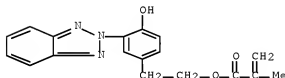
CCI PMS, MAN

*** STRUCTURE DIAGRAM IS NOT AVAILABLE ***

CM 2

CRN 96478-09-0

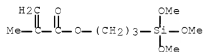
CMF C18 H17 N3 O3



CM 3

CRN 2530-85-0

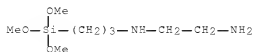
CMF C10 H20 O5 Si



CM 4

CRN 1760-24-3

CMF C8 H22 N2 O3 Si



CM 5

CRN 80-62-6
CMF C5 H8 O2



RN 357166-92-8 HCAPLUS
CN 2-Propenoic acid, 2-methyl-, methyl ester, polymer with
2-[4-(4,6-diphenyl-1,3,5-triazin-2-yl)-3-hydroxyphenoxy]ethyl
2-propenoate, Kaneka MS Polymer S 203,
N-[3-(trimethoxysilyl)propyl]-1,2-ethanediamine and
3-(trimethoxysilyl)propyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

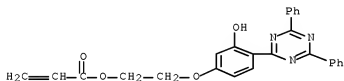
CM 1

CRN 178535-69-8
CMF Unspecified
CCI PMS, MAN

*** STRUCTURE DIAGRAM IS NOT AVAILABLE ***

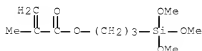
CM 2

CRN 176225-24-4
CMF C26 H21 N3 O4



CM 3

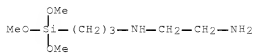
CRN 2530-85-0
CMF C10 H20 O5 Si



CM 4

CRN 1760-24-3

CMF C8 H22 N2 O3 Si



CM 5

CRN 80-62-6

CMF C5 H8 O2



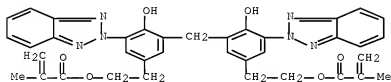
RN 357166-93-9 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, methylenebis[[5-(2H-benzotriazol-2-yl)-4-hydroxy-3,1-phenylene]-2,1-ethanediyl] ester, polymer with Kaneka MS Polymer S 203, methyl 2-methyl-2-propenoate, N-[3-(trimethoxysilyl)propyl]-1,2-ethanediamine and 3-(trimethoxysilyl)propyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 263909-63-3

CMF C37 H34 N6 O6



CM 2

CRN 178535-69-8

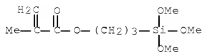
CMF Unspecified

CCI PMS, MAN

*** STRUCTURE DIAGRAM IS NOT AVAILABLE ***

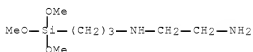
CM 3

CRN 2530-85-0
CMF C10 H20 O5 Si



CM 4

CRN 1760-24-3
CMF C8 H22 N2 O3 Si



CM 5

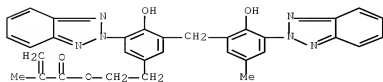
CRN 80-62-6
CMF C5 H8 O2



RN 357166-94-0 HCAPLUS
CN 2-Propenoic acid, 2-methyl-, 2-[3-(2H-benzotriazol-2-yl)-5-[[3-(2H-benzotriazol-2-yl)-2-hydroxy-5-methylphenyl]methyl]-4-hydroxyphenyl]ethyl ester, polymer with Kaneka MS Polymer S 203, methyl 2-methyl-2-propenoate, N-[3-(trimethoxysilyl)propyl]-1,2-ethanediamine and 3-(trimethoxysilyl)propyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 215998-14-4
CMF C32 H28 N6 O4



CM 2

CRN 178535-69-8

CMF Unspecified

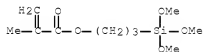
CCI PMS, MAN

*** STRUCTURE DIAGRAM IS NOT AVAILABLE ***

CM 3

CRN 2530-85-0

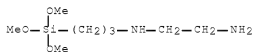
CMF C10 H20 O5 Si



CM 4

CRN 1760-24-3

CMF C8 H22 N2 O3 Si



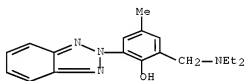
CM 5

CRN 80-62-6

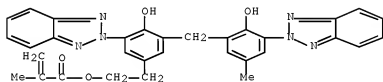
CMF C5 H8 O2



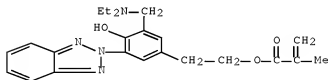
IT 103597-49-5P 215998-14-4P 263909-48-4P
 263909-63-3P
 RL: IMF (Industrial manufacture); RCT (Reactant); PREP (Preparation); RACT
 (Reactant or reagent)
 (room temperature-curable UV absorber-polymerized polyether silicone
 sealants
 with weather resistance)
 RN 103597-49-5 HCAPLUS
 CN Phenol, 2-(2H-benzotriazol-2-yl)-6-[(diethylamino)methyl]-4-methyl- (CA
 INDEX NAME)



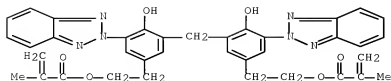
RN 215998-14-4 HCAPLUS
 CN 2-Propenoic acid, 2-methyl-, 2-[3-(2H-benzotriazol-2-yl)-5-[[3-(2H-benzotriazol-2-yl)-2-hydroxy-5-methylphenyl]methyl]-4-hydroxyphenyl]ethyl ester (CA INDEX NAME)



RN 263909-48-4 HCAPLUS
 CN 2-Propenoic acid, 2-methyl-, 2-[3-(2H-benzotriazol-2-yl)-5-[(diethylamino)methyl]-4-hydroxyphenyl]ethyl ester (CA INDEX NAME)



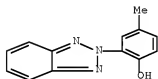
RN 263909-63-3 HCAPLUS
 CN 2-Propenoic acid, 2-methyl-, methylenebis[[5-(2H-benzotriazol-2-yl)-4-hydroxy-3,1-phenylene]-2,1-ethanediyl] ester (9CI) (CA INDEX NAME)



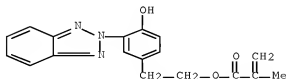
IT 50-00-0, Formaldehyde, reactions 2440-22-4
 96478-09-0, 2-(2'-Hydroxy-5'-methacryloxyethylphenyl)-2H-benzotriazole
 RL: RCT (Reactant); RACT (Reactant or reagent)
 (room temperature-curable UV absorber-polymerized polyether silicone sealants with weather resistance)
 RN 50-00-0 HCAPLUS
 CN Formaldehyde (CA INDEX NAME)



RN 2440-22-4 HCAPLUS
 CN Phenol, 2-(2H-benzotriazol-2-yl)-4-methyl- (CA INDEX NAME)



RN 96478-09-0 HCAPLUS
 CN 2-Propenoic acid, 2-methyl-, 2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl ester (CA INDEX NAME)



L84 ANSWER 12 OF 16 HCAPLUS COPYRIGHT 2009 ACS on STN
 ACCESSION NUMBER: 2001:101050 HCAPLUS [Full-text](#)
 DOCUMENT NUMBER: 134:164625
 TITLE: Recording method comprising printing recording medium with two liquid components

Serial No.:10/582,307

INVENTOR(S): Kubota, Kazuhide; Oyanagi, Takashi; Miyabayashi, Toshiyuki
 PATENT ASSIGNEE(S): Seiko Epson Corp., Japan
 SOURCE: PCT Int. Appl., 137 pp.
 CODEN: PIXXD2
 DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 3
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
WO 2001008895	A1	20010208	WO 2000-JP5150	20000731 <--
W: JP, US				
RW: AT, BE, CH, CY, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE				
EP 1125760	A1	20010822	EP 2000-949945	20000731 <--
EP 1125760	B1	20060517		
R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, FI, CY				
JP 3622910	B2	20050223	JP 2001-513596	20000731 <--
AT 326354	T	20060615	AT 2000-949945	20000731 <--
US 20030069329	A1	20030410	US 2002-56231	20020125 <--
US 7040747	B2	20060509		
PRIORITY APPLN. INFO.:				
			JP 1999-217296	A 19990730 <--
			JP 2000-7135	A 20000114 <--
			JP 2000-211821	A 20000712 <--
			JP 2000-222966	A 20000724 <--
			JP 2000-224002	A 20000725 <--
			JP 2000-224141	A 20000725 <--
			WO 2000-JP5150	W 20000731 <--
			JP 2001-20737	A 20010129 <--
			US 2001-806273	A2 20010328 <--
ED	Entered STN: 09 Feb 2001			
AB	Title recording method for providing a good image with excellent adhesion to a recording medium and friction-resistance comprises printing by using an ink composition comprising a colorant, resin emulsion particles, a water-soluble organic solvent and water, and a reacting liquid comprising a reactant producing a coagulation upon contacting with the above ink composition to adhere to a recording medium, wherein the method comprises the steps of making the reacting liquid to adhere to the recording medium, then attaching the ink composition to the medium to print an image, and washing the recording medium printed with a polar solvent. Thus an ink composition comprising (1) a reacting liquid containing Mg(NO3)2·6H2O, triethylene glycol Bu monoether, glycerin, and ion exchanged water, (2) a black ink composition containing carbon black MA 7, styrene-acrylic acid copolymer, styrene-2-ethylhexyl acrylate-methacrylic acid copolymer-sodium dodecylbenzenesulfonate emulsion, glycerin, and ion exchanged water, and (3) a color ink set containing cyan, magenta, and yellow inks was prepared for printing test, showing good image quality and good adhesion to medium after washing and heating.			
IT	232935-02-3P, Acrylamide-acrylic acid-ADK Stab LA 82-butyl acrylate-RUVA 93-styrene copolymer ammonium salt 324575-78-2P 324575-80-6P 324575-82-8P			
	RL: IMF (Industrial manufacture); POF (Polymer in formulation); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)			
	(emulsion, ink containing; preparation and properties of printing ink composition with two liquid components)			
RN	232935-02-3 HCAPLUS			

CN 2-Propenoic acid, 2-methyl-, 2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl ester, polymer with butyl 2-propenoate, ethenylbenzene, 1,2,2,6,6-pentamethyl-4-piperidiny 2-methyl-2-propenoate, 2-propenamide and 2-propenoic acid, ammonium salt (9CI) (CA INDEX NAME)

CM 1

CRN 215377-65-4

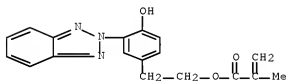
CMF (C18 H17 N3 O3 . C14 H25 N O2 . C8 H8 . C7 H12 O2 . C3 H5 N O . C3 H4 O2)x

CCI PMS

CM 2

CRN 96478-09-0

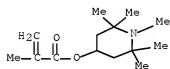
CMF C18 H17 N3 O3



CM 3

CRN 68548-08-3

CMF C14 H25 N O2



CM 4

CRN 141-32-2

CMF C7 H12 O2



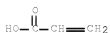
CM 5

CRN 100-42-5
CMF C8 H8



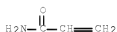
CM 6

CRN 79-10-7
CMF C3 H4 O2



CM 7

CRN 79-06-1
CMF C3 H5 N O



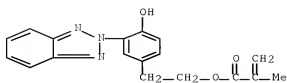
RN 324575-78-2 HCAPLUS
CN 2-Propenoic acid, 2-methyl-, polymer with
2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl 2-methyl-2-propenoate,
butyl 2-propenoate, ethenylbenzene, oxiranylmethyl 2-methyl-2-propenoate,
1,2,2,6,6-pentamethyl-4-piperidiny 2-methyl-2-propenoate and
2-propenamide, ammonium salt (9CI) (CA INDEX NAME)

CM 1

CRN 324575-77-1
CMF (C18 H17 N3 O3 . C14 H25 N O2 . C8 H8 . C7 H12 O2 . C7 H10 O3 . C4 H6
O2 . C3 H5 N O)x
CCI PMS

CM 2

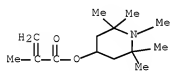
CRN 96478-09-0
CMF C18 H17 N3 O3



CM 3

CRN 68548-08-3

CMF C14 H25 N O2



CM 4

CRN 141-32-2

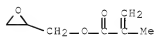
CMF C7 H12 O2



CM 5

CRN 106-91-2

CMF C7 H10 O3



CM 6

CRN 100-42-5

CMF C8 H8



CM 7

CRN 79-41-4

CMF C4 H6 O2



CM 8

CRN 79-06-1

CMF C3 H5 N O



RN 324575-80-6 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 1,2-ethanediyl ester, polymer with
 2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl 2-methyl-2-propenoate,
 butyl 2-propenoate, ethenylbenzene, 1,2,2,6,6-pentamethyl-4-piperidinyl
 2-methyl-2-propenoate, 2-propenamide and 2-propenoic acid, ammonium salt
 (9CI) (CA INDEX NAME)

CM 1

CRN 324575-79-3

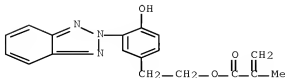
CMF (C18 H17 N3 O3 . C14 H25 N O2 . C10 H14 O4 . C8 H8 . C7 H12 O2 . C3
 H5 N O . C3 H4 O2)x

CCI PMS

CM 2

CRN 96478-09-0

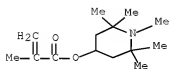
CMF C18 H17 N3 O3



CM 3

CRN 68548-08-3

CMF C14 H25 N O2



CM 4

CRN 141-32-2

CMF C7 H12 O2



CM 5

CRN 100-42-5

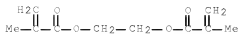
CMF C8 H8



CM 6

CRN 97-90-5

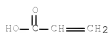
CMF C10 H14 O4



CM 7

CRN 79-10-7

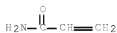
CMF C3 H4 O2



CM 8

CRN 79-06-1

CMF C3 H5 N O



RN 324575-82-8 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, polymer with
 2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl 2-methyl-2-propenoate,
 butyl 2-propenoate, 1,2-ethanediyl bis(2-methyl-2-propenoate),
 ethenylbenzene, oxiranylmethyl 2-methyl-2-propenoate,
 1,2,2,6,6-pentamethyl-4-piperidiny 2-methyl-2-propenoate, 2-propenamide
 and 2-sulfoethyl 2-methyl-2-propenoate sodium salt, ammonium salt (9CI)
 (CA INDEX NAME)

CM 1

CRN 324575-81-7

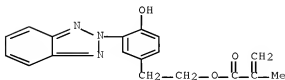
CMF (C18 H17 N3 O3 . C14 H25 N O2 . C10 H14 O4 . C8 H8 . C7 H12 O2 . C7
 H10 O3 . C6 H10 O5 S . C4 H6 O2 . C3 H5 N O . Na)x

CCI PMS

CM 2

CRN 96478-09-0

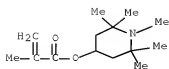
CMF C18 H17 N3 O3



CM 3

CRN 68548-08-3

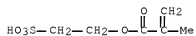
CMF C14 H25 N O2



CM 4

CRN 1804-87-1

CMF C6 H10 O5 S . Na

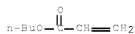


● Na

CM 5

CRN 141-32-2

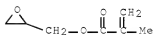
CMF C7 H12 O2



CM 6

CRN 106-91-2

CMF C7 H10 O3



CM 7

CRN 100-42-5

CMF C8 H8



CM 8

CRN 97-90-5

CMF C10 H14 O4



CM 9

CRN 79-41-4

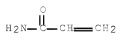
CMF C4 H6 O2



CM 10

CRN 79-06-1

CMF C3 H5 N O



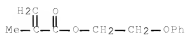
IT 324575-83-9F 324575-84-0P 324737-84-0P, Butyl methacrylate-ethylene oxide-methacrylic acid-phenoxyethyl methacrylate graft copolymer ammonium sulfate
 RL: IMF (Industrial manufacture); POF (Polymer in formulation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses) (pigment dispersion; preparation and properties of printing ink composition with two liquid components)
 RN 324575-83-9 HCAPLUS
 CN 2-Propenenitrile, polymer with α -sulfo- ω -[1-[(4-nonylphenoxy)methyl]-2-(2-propenyloxy)ethoxy]poly(oxy-1,2-ethanediyl) ammonium salt, graft (9CI) (CA INDEX NAME)

CM 1

CM 2

CRN 10595-06-9

CMF C12 H14 O3



CM 3

CRN 97-88-1

CMF C8 H14 O2



CM 4

CRN 79-41-4

CMF C4 H6 O2



RN 324737-84-0 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, polymer with butyl 2-methyl-2-propenoate, oxirane and 2-phenoxyethyl 2-methyl-2-propenoate, hydrogen sulfate, graft, ammonium salt (9CI) (CA INDEX NAME)

CM 1

CRN 7664-93-9

CMF H2 O4 S



CM 2

CRN 324737-83-9

CMF (C12 H14 O3 . C8 H14 O2 . C4 H6 O2 . C2 H4 O)x

CCI PMS

CM 3

CRN 10595-06-9

CMF C12 H14 O3



CM 4

CRN 97-88-1

CMF C8 H14 O2



CM 5

CRN 79-41-4

CMF C4 H6 O2



CM 6

CRN 75-21-8

CMF C2 H4 O



L84 ANSWER 13 OF 16 HCAPLUS COPYRIGHT 2009 ACS on STN
 ACCESSION NUMBER: 2001:28673 HCAPLUS Full-text
 DOCUMENT NUMBER: 134:102179
 TITLE: Polymers for imparting light resistance to fibers,
 highly light-resistant fibers, and their production
 INVENTOR(S): Nishida, Toshifumi; Noda, Nobuhisa; Aoyama, Takahiro
 PATENT ASSIGNEE(S): Nippon Shokubai Co., Ltd., Japan
 SOURCE: Eur. Pat. Appl., 17 pp.
 CODEN: EPXXDW
 DOCUMENT TYPE: Patent
 LANGUAGE: English
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
EP 1067223	A1	20010110	EP 2000-114042	20000705 <--
EP 1067223	B1	20050406		
R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO				
JP 2001019716	A	20010123	JP 1999-196567	19990709 <--
JP 4220620	B2	20090204		
CN 1280214	A	20010117	CN 2000-109566	20000705 <--
CN 1163641	C	20040825		
US 6312802	B1	20011106	US 2000-612213	20000707 <--
			JP 1999-196567	A 19990709 <--

PRIORITY APPLN. INFO.:

ED Entered STN: 12 Jan 2001

AB A polymer for imparting light resistance to fibers is prepared by radically polymerizing a monomer composition including a specific UV stabilizable monomer and/or UV absorptive monomer. A highly light-resistant fiber includes the light resistance imparting polymer inside or on the surface of the fiber. A coating solution (PhMe) of hydroxymethacryloyloxyethylphenyl benzotriazole-cyclohexane methacrylate-4-methacryloyloxy-2,2,6,6-tetramethylpiperidine copolymer (10:20:60) was used for dipping of polyurethaneurea fiber followed by heat drying. The coated fiber had strength retention ratio 71% and 69% after humid storage, and yellowing resistance δb 6.5.

IT 204390-80-7P 319012-83-4P 319012-86-7P

RL: IMF (Industrial manufacture); PEP (Physical, engineering or chemical process); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); PROC (Process); USES (Uses)
 (bicomponent with fibers; polymer fibers or coatings for imparting light resistance to fibers)

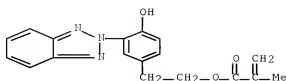
RN 204390-80-7 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl ester, polymer with cyclohexyl 2-methyl-2-propenoate and 2,2,6,6-tetramethyl-4-piperidinyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 96478-09-0

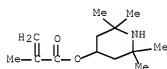
CMF C18 H17 N3 O3



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CRN 31582-45-3

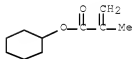
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CM 3

CRN 101-43-9

CMF C10 H16 O2



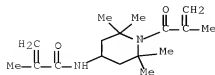
RN 319012-83-4 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, butyl ester, polymer with
 2-[3-(1,1-dimethylethyl)-5-[4-(1,1-dimethylethyl)-2H-benzotriazol-2-yl]-4-
 hydroxyphenoxy]ethyl 2-methyl-2-propenoate, methyl 2-methyl-2-propenoate
 and 2-methyl-N-[2,2,6,6-tetramethyl-1-(2-methyl-1-oxo-2-propenyl)-4-
 piperidinyl]-2-propenamide (9CI) (CA INDEX NAME)

CM 1

CRN 187231-12-5

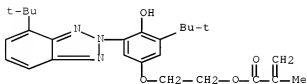
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CM 2

CRN 159301-33-4

CMF C26 H33 N3 O4



CM 3

CRN 97-88-1

CMF C8 H14 O2



CM 4

CRN 80-62-6

CMF C5 H8 O2



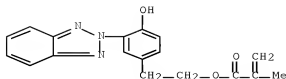
RN 319012-86-7 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl ester, polymer with butyl 2-propenoate and cyclohexyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 96478-09-0

CMF C18 H17 N3 O3



CM 2

CRN 141-32-2

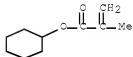
CMF C7 H12 O2



CM 3

CRN 101-43-9

CMF C10 H16 O2



REFERENCE COUNT: 5 THERE ARE 5 CITED REFERENCES AVAILABLE FOR THIS
RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L84 ANSWER 14 OF 16 HCAPLUS COPYRIGHT 2009 ACS on STN
 ACCESSION NUMBER: 1998:149617 HCAPLUS [Full-text](#)
 DOCUMENT NUMBER: 128:231082
 ORIGINAL REFERENCE NO.: 128:45769a, 45772a
 TITLE: Weather-resistant polyurea-polyurethane compositions
 INVENTOR(S): Morito, Yoshinori
 PATENT ASSIGNEE(S): Asahi Chemical Industry Co., Ltd., Japan
 SOURCE: Jpn. Kokai Tokkyo Koho, 6 pp.
 CODEN: JKXXAF
 DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 10060262	A	19980303	JP 1996-222144	19960823 <--
PRIORITY APPLN. INFO.:			JP 1996-222144	19960823 <--

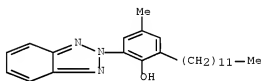
ED Entered STN: 12 Mar 1998

AB The title comps. comprise polyurea-polyurethanes (e.g., ethylenediamine-MDI-polytetramethylene glycol copolymer), hindered phenol compds. (e.g., reaction product of p-cresol-dicyclopentadiene copolymer and isobutylene), polyurethanes containing tertiary amino groups (e.g., N-butyl-N,N-diethanolamine-isophorone diisocyanate copolymer), and 0.3-3.0% benzotriazole compds. (e.g., Tinuvin 571, Tinuvin 213).

IT 23328-53-2, Tinuvin 571 136457-10-8, Tinuvin 213
 RL: MOA (Modifier or additive use); TEM (Technical or engineered material use); USES (Uses)
 (UV absorbents; weather-resistant polyurea-polyurethane compns.)

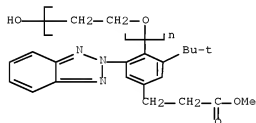
RN 23328-53-2 HCAPLUS

CN Phenol, 2-(2H-benzotriazol-2-yl)-6-dodecyl-4-methyl- (CA INDEX NAME)



RN 136457-10-8 HCAPLUS

CN Poly(oxy-1,2-ethanediyl), α-[2-(2H-benzotriazol-2-yl)-6-(1,1-dimethylethyl)-4-(3-methoxy-3-oxopropyl)phenyl]-ω-hydroxy- (CA INDEX NAME)



L84 ANSWER 15 OF 16 HCAPLUS COPYRIGHT 2009 ACS on STN

ACCESSION NUMBER: 1997:211184 HCAPLUS [Full-text](#)

DOCUMENT NUMBER: 126:200631

ORIGINAL REFERENCE NO.: 126:38773a, 38776a

TITLE: UV absorber compositions for manufacture of dyed or

printed fibers with good lightfastness and leveling

Best, Michael; Murat, Jean-Luc; Palacin, Francis

PATENT ASSIGNEE(S): Clariant Finance (Bvi) Limited, UK;

Sandoz-Patent-GmbH; Sandoz-Erfindungen

Verwaltungsgesellschaft M.B.H.; Best, Michael; Murat,

Jean-Luc; Palacin, Francis

SOURCE: PCT Int. Appl., 24 pp.

CODEN: PIXXD2

DOCUMENT TYPE: Patent

LANGUAGE: English

FAMILY ACC. NUM. COUNT: 2

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
WO 9703242	A1	19970130	WO 1996-EP3050	19960711 <--
W: BR, JP, US				
RW: AT, BE, CH, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE				
GB 2308847	A	19970709	GB 1995-26206	19951221 <--
EP 842319	A1	19980520	EP 1996-925729	19960711 <--
EP 842319	B1	20010516		
R: AT, BE, CH, DE, DK, ES, FR, GB, IT, LI, SE, FI				
BR 9609728	A	19990511	BR 1996-9728	19960711 <--
JP 11508935	T	19990803	JP 1996-505507	19960711 <--
ES 2158328	T3	20010901	ES 1996-925729	19960711 <--
PRIORITY APPLN. INFO.:				
			US 1995-501335	A 19950712 <--
			GB 1995-26206	A 19951221 <--
			WO 1996-EP3050	W 19960711 <--

ED Entered STN: 02 Apr 1997

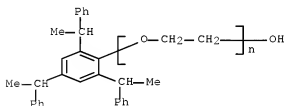
AB The comps. comprise 20-45% 2-(2'-hydroxyphenyl)benzotriazoles as light stabilizers, 7-25% condensates of sulfonated tolyl ether and HCHO, and 0.5-10% addition products of ethylene oxide and/or propylene oxide and C7-20 fatty alcs., C7-20 fatty acids, C7-20 fatty amides, C7-20 fatty esters, tristyrilphenol, and/or distyrylphenol as nonionic surfactants and H2O, have good storage stability, and show excellent shear stability when the substrate to be dyed is a yarn which is in the packed form. Thus, 2-(2'-hydroxy-3'-tert-butyl-5'-methylphenyl)-5-chlorobenzotriazole 25.0, dioleil ether sulfonate-HCHO condensate (Baykanol SL) 14.0, propylene glycol-propylene oxide-ethylene oxide adduct (Pluronic P 75) 1.20, ethoxylated tristyrilphenol (Soprophor BSU) 4.0, wetting agent 1.0, GivGard (conservation agent) 0.20, NaOH 0.05, and H2O 54.55 parts were mixed to give a dispersion (A). A polyester fabric was dyed with an aqueous composition containing 0.75% C.I. Disperse Red 74 and 0.75% A dispersion in an autoclave for 20 min at 135° to give a fabric exhibiting excellent lightfastness and good leveling.

IT 70559-25-0, Soprophor BSU

RL: MOA (Modifier or additive use); PRP (Properties); USES (Uses) (leveling agent; UV absorber comps. for manufacture of dyed or printed fibers with good lightfastness and leveling containing)

RN 70559-25-0 HCAPLUS

CN Poly(oxy-1,2-ethanediyl), α -[2,4,6-tris(1-phenylethyl)phenyl]- ω -hydroxy- (CA INDEX NAME)

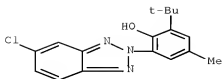


IT 3896-11-5

RL: MOA (Modifier or additive use); PRP (Properties); USES (Uses) (light stabilizer; UV absorber comps. for manufacture of dyed or printed fibers with good lightfastness and leveling)

RN 3896-11-5 HCAPLUS

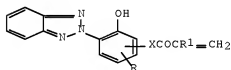
CN Phenol, 2-(5-chloro-2H-benzotriazol-2-yl)-6-(1,1-dimethylethyl)-4-methyl- (CA INDEX NAME)



REFERENCE COUNT: 6 THERE ARE 6 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L84 ANSWER 16 OF 16 HCAPLUS COPYRIGHT 2009 ACS on STN
 ACCESSION NUMBER: 1989:194760 HCAPLUS Full-text
 DOCUMENT NUMBER: 110:194760
 ORIGINAL REFERENCE NO.: 110:32337a,32340a
 TITLE: Benzotriazole light stabilizers for thermosetting resin coatings
 INVENTOR(S): Yagi, Masaki; Nakahara, Yutaka; Takatori, Katsuyuki; Nakajima, Toshio
 PATENT ASSIGNEE(S): Adeka Argus Chemical Co., Ltd., Japan
 SOURCE: Jpn. Kokai Tokkyo Koho, 6 pp.
 CODEN: JKXXAF
 DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 63205334	A	19880824	JP 1987-36935	19870220
PRIORITY APPLN. INFO.:			JP 1987-36935	19870220
ED Entered STN: 26 May 1989				
GI				

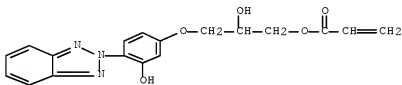


I

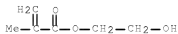
AB Title stabilizers are composed of benzotriazoles I [R = H, alkyl; R1 = H, Me; X = O, CH2NH, OCH2CH2O, OCH2CH(OH)CH2O, CH2O, CH2CH2O, CH2CH2CO2CH2CH2O, CH2CH2CO2CH2CH(OH)CH2O]. A primed steel plate was sprayed with a base coating composition containing Bu acrylate (II)-2-hydroxyethyl methacrylate (III)-methacrylic acid (IV)-Me methacrylate (V) copolymer, U-Van 20SE60, cellulose acetate butyrate, Alpaste 1123N, xylene, AcOBu, and Cu phthalocyanine blue, left for 10 min, sprayed with a top coating composition containing II-III-IV-V-[2-hydroxy-3-(acryloylaminomethyl)-5- methylphenyl]benzotriazole (VI) copolymer, U-Van 20SE60, xylene, and Bu glycol acetate, and baked 30 min at 140° to form a coating, which cracked after 2500 h in weather-o-meter test, vs., 1600 for the coating prepared without VI.

Serial No.:10/582,307

IT 120303-74-4 120326-77-4 120326-80-9
 RL: TEM (Technical or engineered material use); USES (Uses)
 (coatings, weather-resistant)
 RN 120303-74-4 HCAPLUS
 CN 2-Propenoic acid, 2-methyl-, polymer with
 3-[4-(2H-benzotriazol-2-yl)-3-hydroxyphenoxy]-2-hydroxypropyl
 2-propenoate, butyl 2-propenoate, formaldehyde, 2-hydroxyethyl
 2-methyl-2-propenoate, methyl 2-methyl-2-propenoate and
 1,3,5-triazine-2,4,6-triamine (9CI) (CA INDEX NAME)
 CM 1
 CRN 25177-21-3
 CMF C18 H17 N3 O5



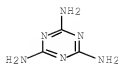
CM 2
 CRN 868-77-9
 CMF C6 H10 O3



CM 3
 CRN 141-32-2
 CMF C7 H12 O2



CM 4
 CRN 108-78-1
 CMF C3 H6 N6



CM 5

CRN 80-62-6

CMF C5 H8 O2



CM 6

CRN 79-41-4

CMF C4 H6 O2



CM 7

CRN 50-00-0

CMF C H2 O



RN 120326-77-4 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, polymer with
 3-[4-(2H-benzotriazol-2-yl)-3-hydroxyphenoxy]-2-hydroxypropyl
 2-methyl-2-propenoate, butyl 2-propenoate, ethenylbenzene, 2-ethylhexyl
 2-methyl-2-propenoate, formaldehyde, 2-hydroxyethyl 2-methyl-2-propenoate,
 Mark EP 13, methyl 2-methyl-2-propenoate and 1,3,5-triazine-2,4,6-triamine
 (9CI) (CA INDEX NAME)

CM 1

CRN 77537-89-4

CMF Unspecified

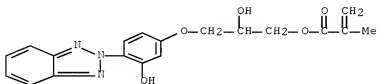
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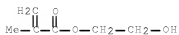
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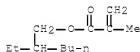
CMF C6 H10 O3



CM 4

CRN 688-84-6

CMF C12 H22 O2



CM 5

CRN 141-32-2

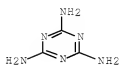
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CM 6

CRN 108-78-1

CMF C3 H6 N6



CM 7

CRN 100-42-5

CMF C8 H8



CM 8

CRN 80-62-6

CMF C5 H8 O2



CM 9

CRN 79-41-4

CMF C4 H6 O2



CM 10

CRN 50-00-0

CMF C H2 O

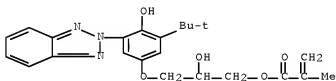


RN 120326-80-9 HCAPLUS
 CN 2-Propenoic acid, 2-methyl-, polymer with
 3-[3-(2H-benzotriazol-2-yl)-5-(1,1-dimethylethyl)-4-hydroxyphenoxy]-2-hydroxypropyl 2-methyl-2-propenoate, butyl 2-propenoate, ethenylbenzene, 2-ethylhexyl 2-methyl-2-propenoate, formaldehyde, 2-hydroxyethyl 2-methyl-2-propenoate, Mark EP 13, methyl 2-methyl-2-propenoate and 1,3,5-triazine-2,4,6-triamine (9CI) (CA INDEX NAME)

CM 1

CRN 120284-06-2

CMF C23 H27 N3 O5



CM 2

CRN 77537-89-4

CMF Unspecified

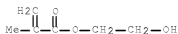
CCI PMS, MAN

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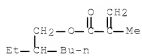
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CM 4

CRN 688-84-6

CMF C12 H22 O2



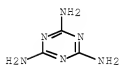
CM 5

CRN 141-32-2
CMF C7 H12 O2



CM 6

CRN 108-78-1
CMF C3 H6 N6



CM 7

CRN 100-42-5
CMF C8 H8



CM 8

CRN 80-62-6
CMF C5 H8 O2



CM 9

CRN 79-41-4
CMF C4 H6 O2



CM 10

CRN 50-00-0
CMF C H2 O



Search History

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L1      1 SEA SPE=ON  ABB=ON  PLU=ON  US2007-582307/APPS

FILE 'REGISTRY' ENTERED AT 08:36:29 ON 18 APR 2009
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      28299-41-4/BI OR 290-87-9/BI OR 3896-11-5/BI OR 613-79-6/BI OR
      70559-25-0/BI OR 91-20-3/BI OR 95-14-7/BI)
L3      STRUCTURE UPLOADED
L4      50 SEA SSS SAM L3
L5      STRUCTURE UPLOADED
L6      STRUCTURE UPLOADED
L7      50 SEA SSS SAM L5 AND L6
L8      STRUCTURE UPLOADED
L9      50 SEA SSS SAM L8
L10     STRUCTURE UPLOADED
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L12     0 SEA SPE=ON  ABB=ON  PLU=ON  L11 AND L2
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L14     50 SEA SSS SAM L13 AND L10
L15     0 SEA SPE=ON  ABB=ON  PLU=ON  L14 AND L2
L16     43152 SEA SSS FUL L13 AND L10
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L18     1 SEA SPE=ON  ABB=ON  PLU=ON  FORMALDEHYDE/CN
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L19     28562 SEA SPE=ON  ABB=ON  PLU=ON  50-00-0/CRN
L20     41 SEA SPE=ON  ABB=ON  PLU=ON  C H2 O/MF
L21     182 SEA SPE=ON  ABB=ON  PLU=ON  C H2 O .?/MF

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L23     80569 SEA SPE=ON  ABB=ON  PLU=ON  L18
L24     95297 SEA SPE=ON  ABB=ON  PLU=ON  L19
L25     647 SEA SPE=ON  ABB=ON  PLU=ON  L22 AND L23
L26     4813 SEA SPE=ON  ABB=ON  PLU=ON  L22 AND L24

FILE 'REGISTRY' ENTERED AT 08:51:31 ON 18 APR 2009
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L28     661 SEA SPE=ON  ABB=ON  PLU=ON  L16 AND L19
L29     0 SEA SPE=ON  ABB=ON  PLU=ON  L16 AND (L20 OR L21)

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L34     STRUCTURE UPLOADED
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Serial No.:10/582,307

L36 41740 SEA SUB=L16 SSS FUL L34
 L37 652 SEA SPE=ON ABB=ON PLU=ON L36 AND (L18 OR L19)
 L38 0 SEA SPE=ON ABB=ON PLU=ON L37 AND L2

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 L41 0 SEA SPE=ON ABB=ON PLU=ON L40 AND L1
 L42 1 SEA SPE=ON ABB=ON PLU=ON L39 AND L1
 L43 640 SEA SPE=ON ABB=ON PLU=ON L39 AND L23
 L44 1 SEA SPE=ON ABB=ON PLU=ON L43 AND L1
 L45 4782 SEA SPE=ON ABB=ON PLU=ON L39 AND L24
 L46 0 SEA SPE=ON ABB=ON PLU=ON L45 AND L1

 FILE 'REGISTRY' ENTERED AT 09:04:37 ON 18 APR 2009
 L47 1 SEA SPE=ON ABB=ON PLU=ON 28299-41-4/RN

 FILE 'HCAPLUS' ENTERED AT 09:04:58 ON 18 APR 2009
 L48 536 SEA SPE=ON ABB=ON PLU=ON L43 AND (PRY<=2004 OR AY<=2004 OR
 PY<=2004)

 FILE 'REGISTRY' ENTERED AT 09:06:57 ON 18 APR 2009
 L49 23942 SEA SPE=ON ABB=ON PLU=ON 333.415.11/RID
 L50 21464 SEA SPE=ON ABB=ON PLU=ON L49 AND 46.150.18/RID
 L51 3 SEA SPE=ON ABB=ON PLU=ON L37 AND L50

 FILE 'HCAPLUS' ENTERED AT 09:09:34 ON 18 APR 2009
 L52 1 SEA SPE=ON ABB=ON PLU=ON L51
 L53 10161 SEA SPE=ON ABB=ON PLU=ON L50
 L54 3 SEA SPE=ON ABB=ON PLU=ON L48 AND L53
 L55 591 SEA SPE=ON ABB=ON PLU=ON L22 AND L53
 L56 519 SEA SPE=ON ABB=ON PLU=ON L55 AND (PRY<=2004 OR AY<=2004 OR
 PY<=2004)
 L57 587 SEA SPE=ON ABB=ON PLU=ON L36 AND L53
 L58 515 SEA SPE=ON ABB=ON PLU=ON L57 AND (PRY<=2004 OR AY<=2004 OR
 PY<=2004)

 FILE 'REGISTRY' ENTERED AT 09:15:28 ON 18 APR 2009
 L59 20674 SEA SPE=ON ABB=ON PLU=ON L50 AND O>=1

 FILE 'HCAPLUS' ENTERED AT 09:15:48 ON 18 APR 2009
 L60 10000 SEA SPE=ON ABB=ON PLU=ON L59
 L61 590 SEA SPE=ON ABB=ON PLU=ON (L22 OR L36) AND L60

 L62 6707 SEA SPE=ON ABB=ON PLU=ON UV STABILIZERS/CT
 L63 163 SEA SPE=ON ABB=ON PLU=ON L58 AND L62
 L64 1560 SEA SPE=ON ABB=ON PLU=ON DISPERSE DYES/CT
 L65 2052 SEA SPE=ON ABB=ON PLU=ON DISPERSE DYES+RT/CT
 L66 24655 SEA SPE=ON ABB=ON PLU=ON DISPERSE AGENTS/CT
 L67 1 SEA SPE=ON ABB=ON PLU=ON L63 AND L65
 L68 1 SEA SPE=ON ABB=ON PLU=ON L63 AND L67
 L69 1 SEA SPE=ON ABB=ON PLU=ON L58 AND L65 AND L66
 L70 6 SEA SPE=ON ABB=ON PLU=ON L58 AND (L65 OR L66)
 L71 9 SEA SPE=ON ABB=ON PLU=ON L63 AND 40/SC, SX
 L72 494 SEA SPE=ON ABB=ON PLU=ON BAILEY B?/AU
 L73 459 SEA SPE=ON ABB=ON PLU=ON GRIFFIN B?/AU
 L74 218 SEA SPE=ON ABB=ON PLU=ON LYONS B?/AU
 L75 3927 SEA SPE=ON ABB=ON PLU=ON WEBER M?/AU
 L76 1 SEA SPE=ON ABB=ON PLU=ON SARETTO B?/AU

L77	9	SEA SPE=ON	ABB=ON	PLU=ON	SCHLINGMANN H7/AU
L78	260	SEA SPE=ON	ABB=ON	PLU=ON	MAHLER G7/AU
L79	1	SEA SPE=ON	ABB=ON	PLU=ON	(L72 OR L73 OR L74 OR L75 OR L76 OR L77 OR L78) AND (L52 OR L54 OR L70 OR L71 OR L67 OR L68 OR L69)
L80	117	SEA SPE=ON	ABB=ON	PLU=ON	L63 AND PREP/RL
L81	163	SEA SPE=ON	ABB=ON	PLU=ON	L63 AND USES/RL S L63 AND PMS/CI

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      FILE 'HCAPLUS' ENTERED AT 09:36:29 ON 18 APR 2009
L83      17 SEA SPE=ON ABB=ON PLU=ON (L67 OR L68 OR L69 OR L52 OR L54
      OR L70 OR L71)
L84      16 SEA SPE=ON ABB=ON PLU=ON L83 NOT L79

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